

Growth and characterization of Chalcogenides-based compounds:

Heterostructures and novel materials

Supervisor
Prof. Fabrizio Arciprete

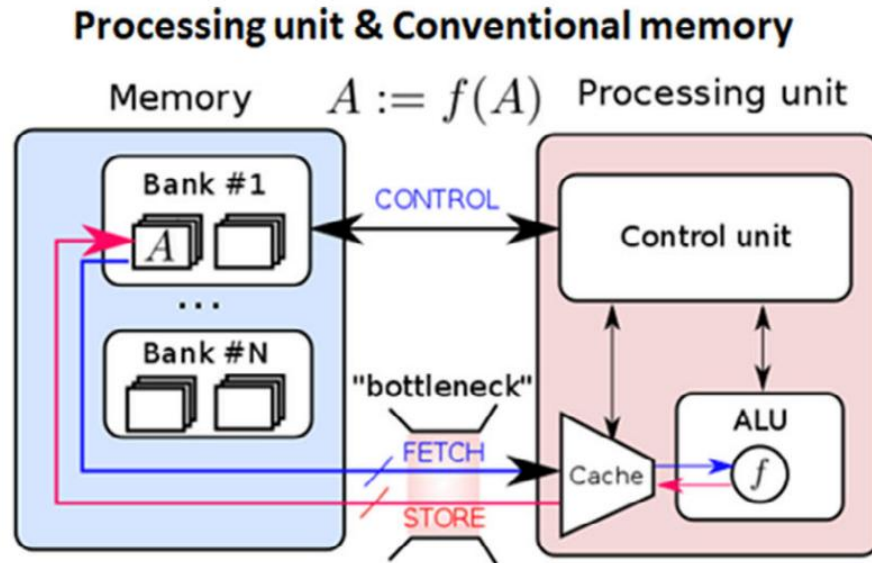
Christian Petrucci
Ph.D. Student
XXXIX° Cycle

Outlook

- **Introduction**
- Experimental setup
- Results
 - Ti doped Ge-Sb-Te alloy
 - In-Ge-Te alloy
- Conclusion

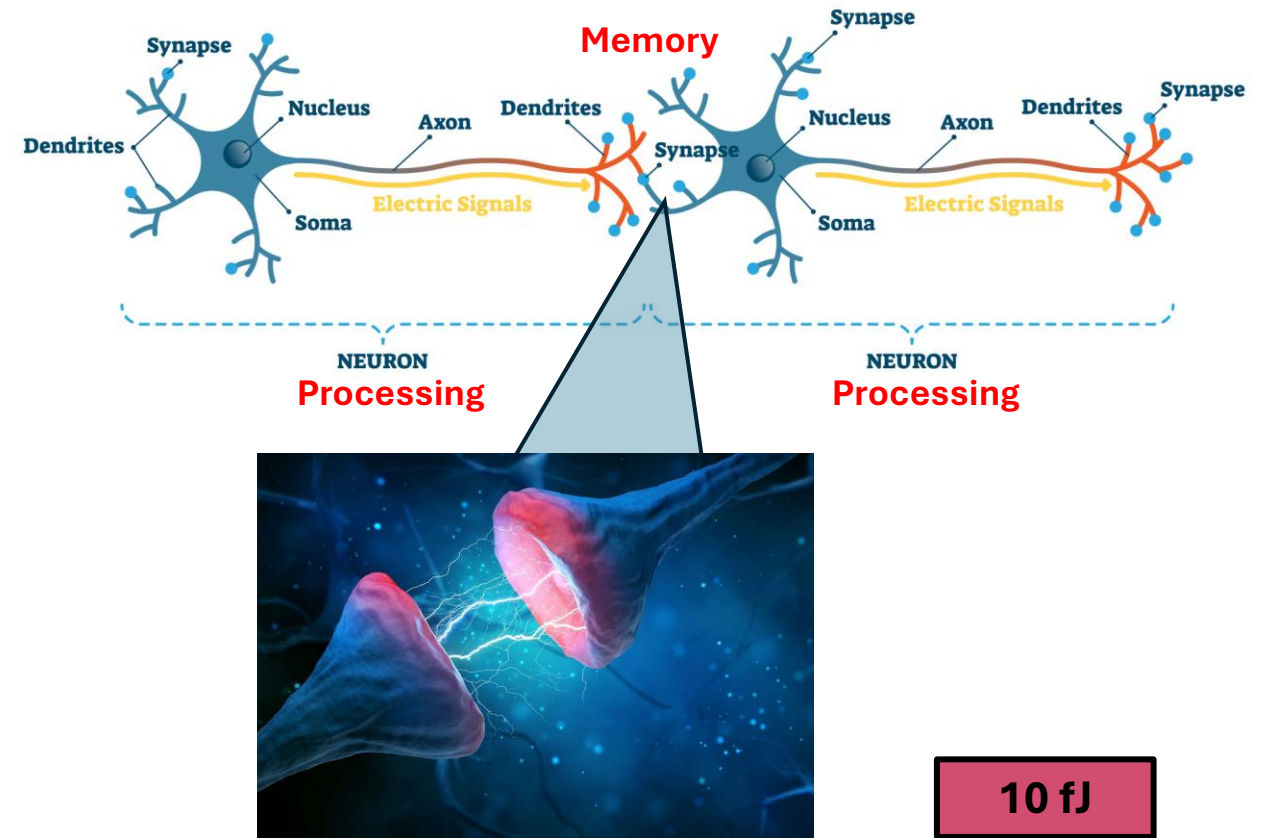
Neuromorphic Computing

<https://www.simplypsychology.org/synapse.html>

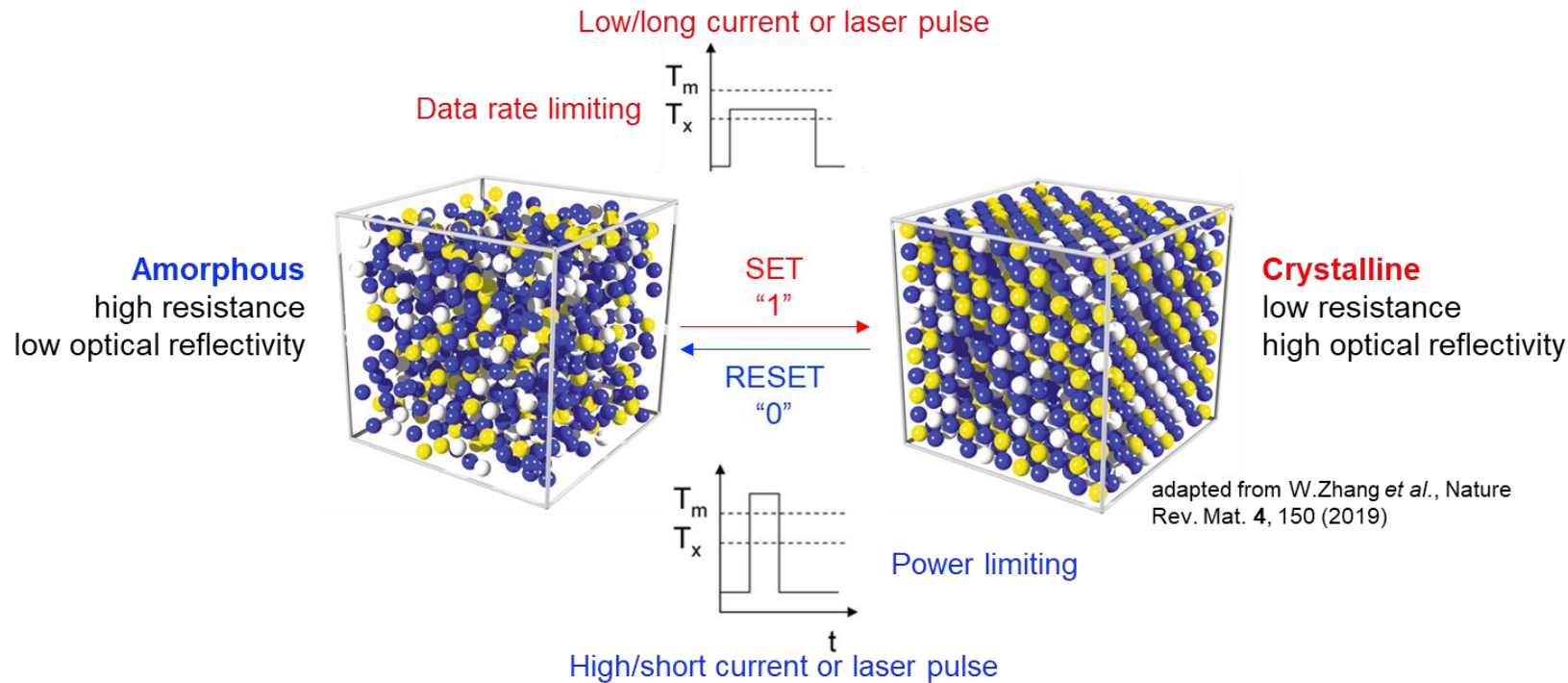


- High power consumption
- Heavy processing of big data

10 pJ



Phase Change Materials

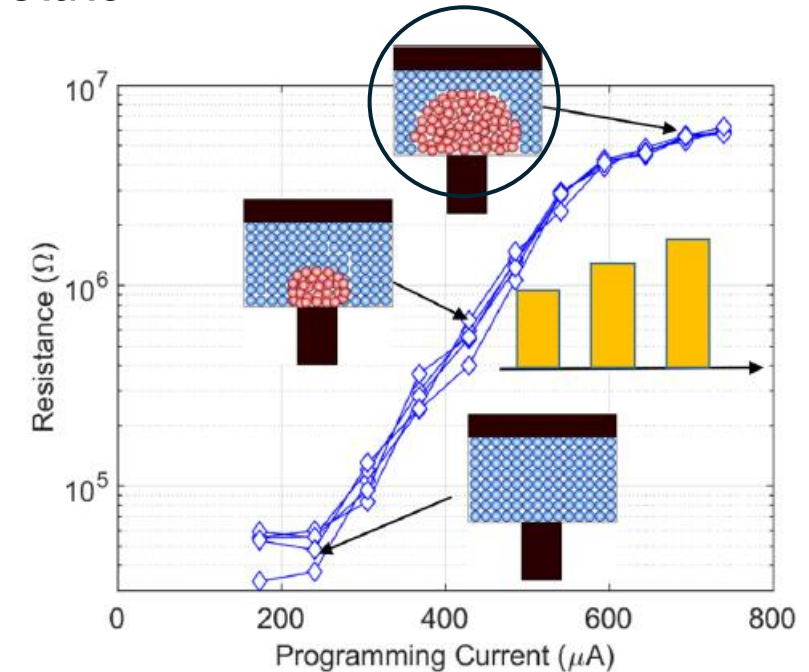


- Used in non-volatile Random Access Memory

PCMs issues:

- Resistance drift over time
- High energy consumption

Programmable region: resistance range depending on the amount of material in amorphous/crystalline state

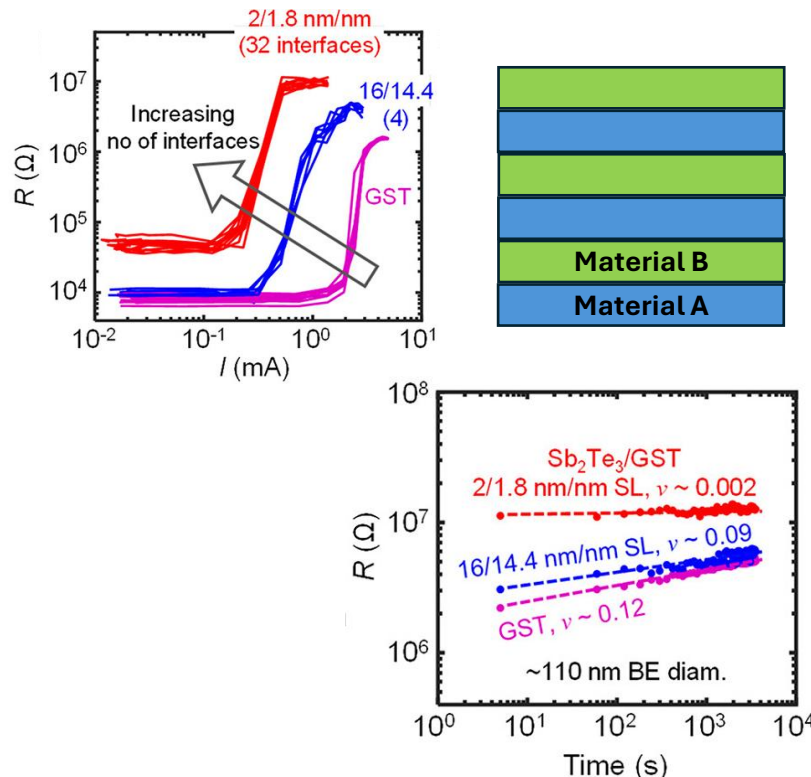


Adapted from: A. Sebastian *et al* «Tutorial: Brain-inspired computing using phase-change memory devices», *J. Appl. Phys.*, vol. 124, fasc. 11, p. 111101, set. 2018

Phase Change Heterostructures

Interfacial PCM

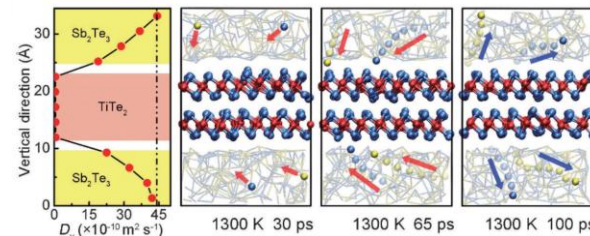
- Lowering of R_{drift} and I_{reset} increasing interfaces number
- Role of **vdW** gap



- PCM/TMDs heterostructures: TiTe_2 as **Confinement Material** (CM)
- Sharp interfaces to prevent atoms **migration** and to **confine heat**

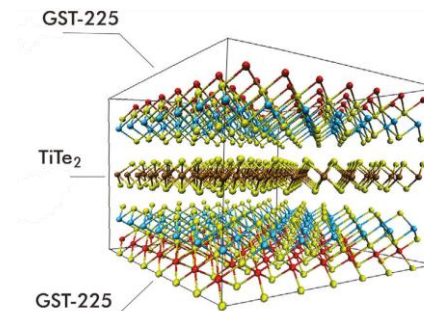
$\text{Sb}_2\text{Te}_3/\text{TiTe}_2$

Ding, K. et al., Science **366**, 210 (2019)



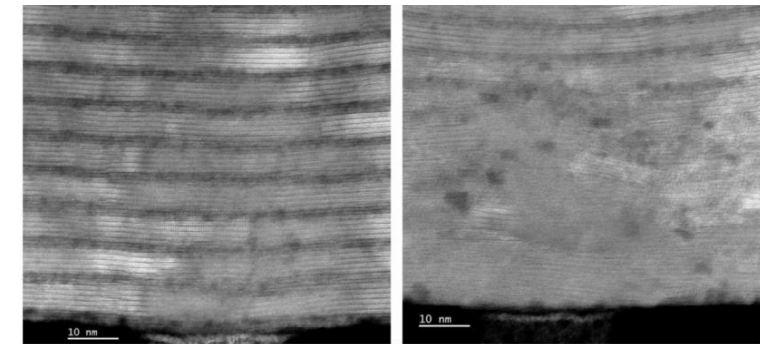
GST/TiTe_2

Piombo, R. et al., Adv. Sci. 2402375 (2024)

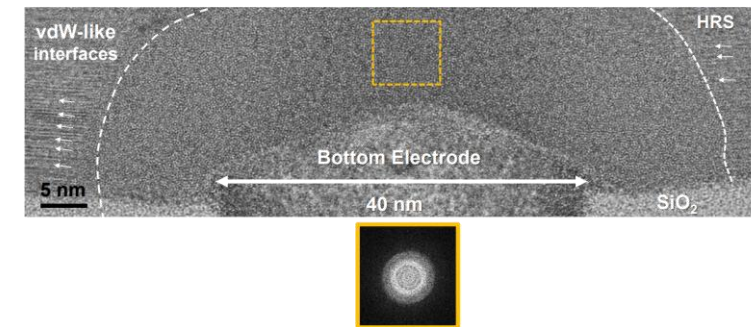


Wu, X et al. Nature Comm. **15**, 13 (2024)

- Strong **Ti migration** and **segregation**



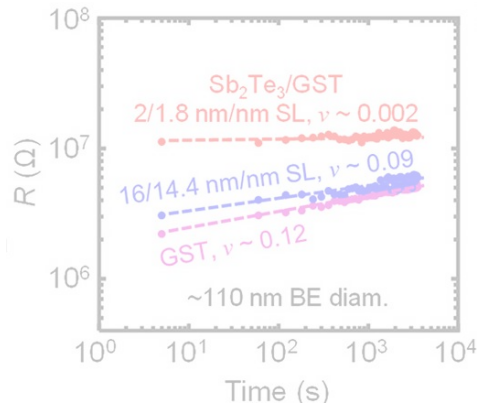
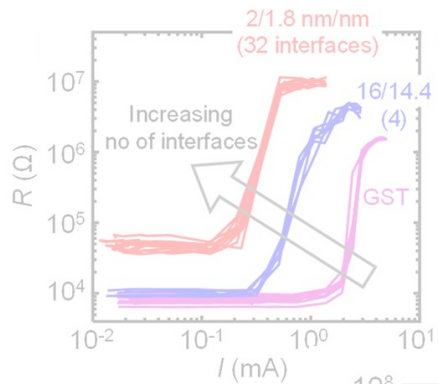
Cohen, G.M. et al., PSS RRL 2300426 (2024)



Phase Change Heterostructures

Interfacial PCM

- Lowering of R_{drift} and I_{reset} increasing interfaces number

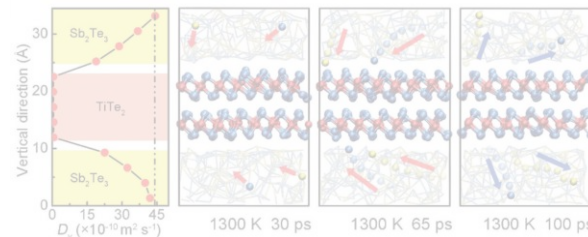


Khan, A. I. *et al.*, Nano Lett. **22**, 6285 (2022)

- PCM/TMDs heterostructures: TiTe_2 as **Confinement Material (CM)**
- Sharp interfaces to prevent atoms migration and to **confine heat**

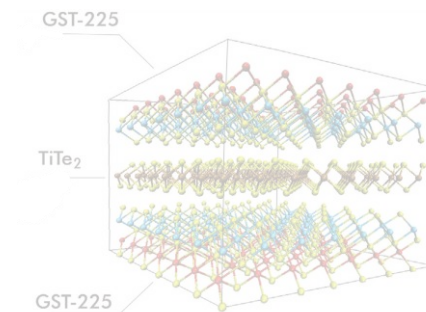
$\text{Sb}_2\text{Te}_3/\text{TiTe}_2$

Ding, K. *et al.*, Science **366**, 210 (2019)



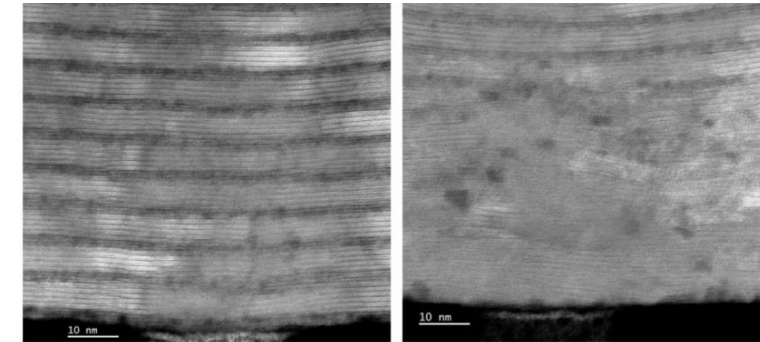
GST/TiTe_2

Piombo, R. *et al.*, Adv. Sci. 2402375 (2024)

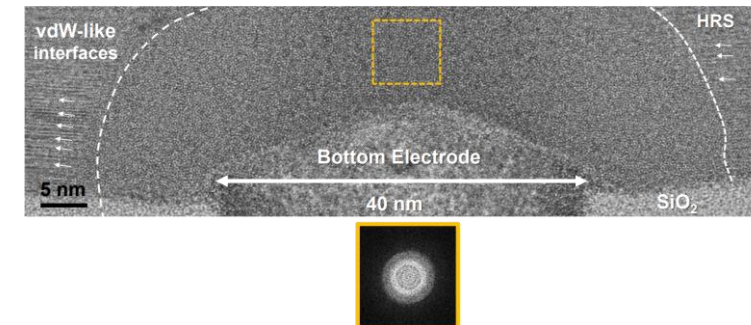


Wu, X *et al.* Nature Comm. **15**, 13 (2024)

- Strong Ti **migration** and **segregation**



Cohen, G.M. *et al.*, PSS RRL 2300426 (2024)



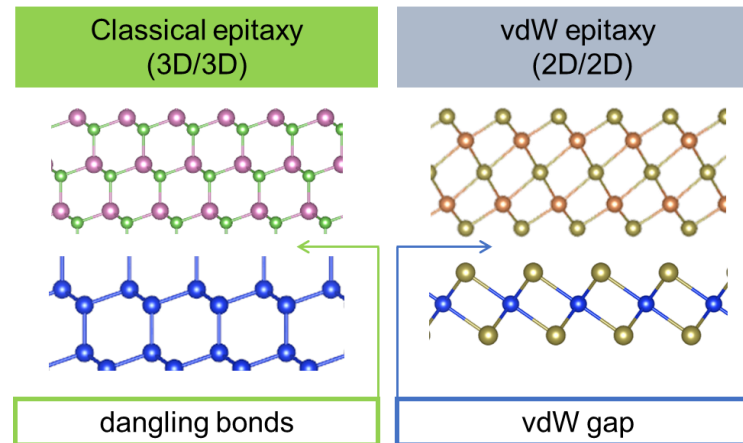
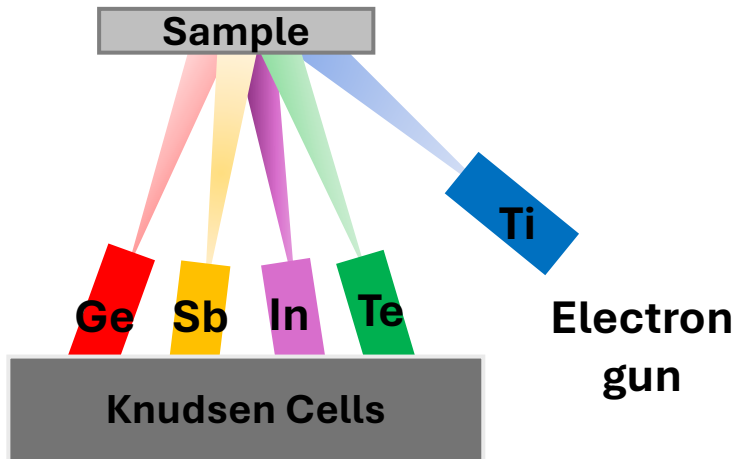
Not perfect interface!

Outlook

- Introduction
- **Experimental setup**
- Results
 - Ti-Ge-Sb-Te alloy
 - In-Ge-Te alloy
- Conclusion

Experimental setup

- Growth via **Molecular Beam Epitaxy**
 - Molecular regime: no interaction before absorption on substrate
 - Co-evaporation of different elements : Ge, Sb, Te, In, Ti
 - Realization of high quality crystalline samples
- **Van der Waals** epitaxy: exploitation of vdW gaps inside materials to allow a less costrictive growth (mismatch allowed up to 45%)



Koma, et al. (1992)

Materials growth rates:

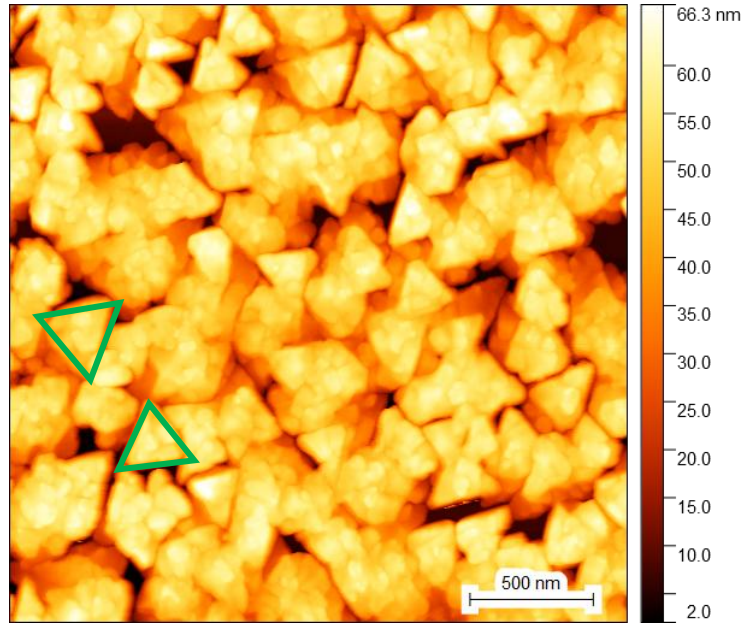
- **TiTe₂** : 0.1 nm/min
- **Sb₂Te₃** : 0.6 nm/min
- **GST** : 0.7 nm/min
- **IGT** : 0.7 nm/min

Outlook

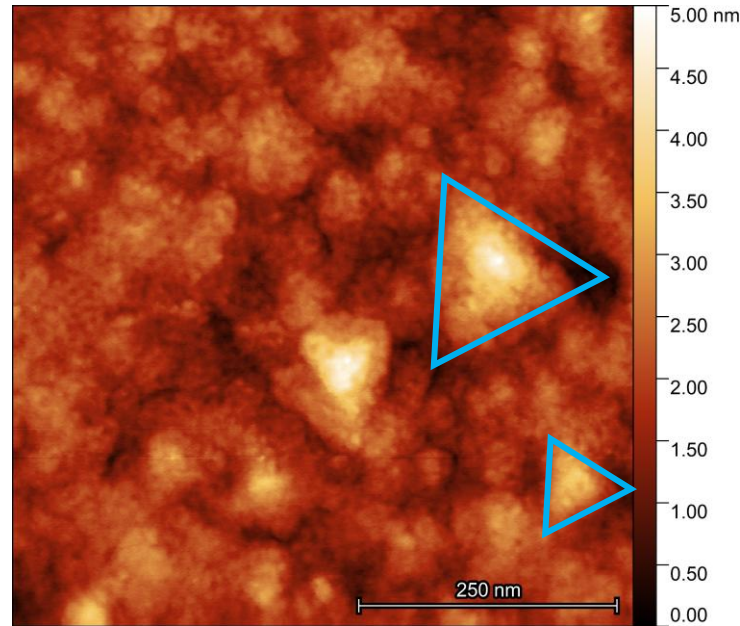
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Epitaxial films growth

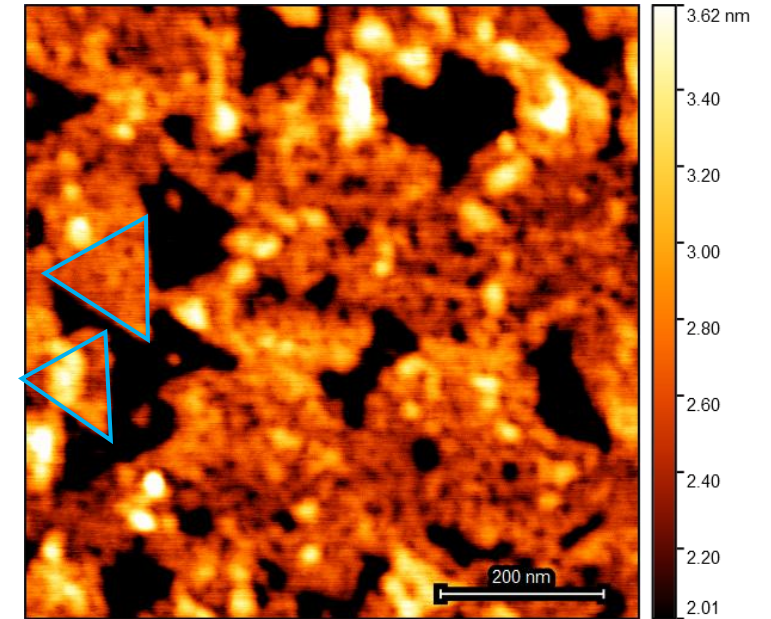
• Sb_2Te_3



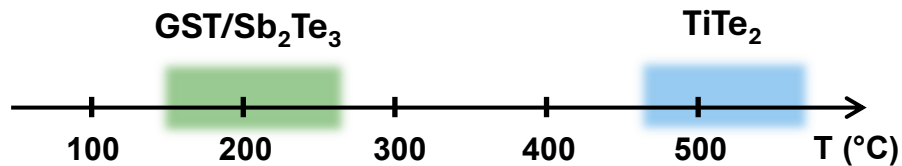
• GST



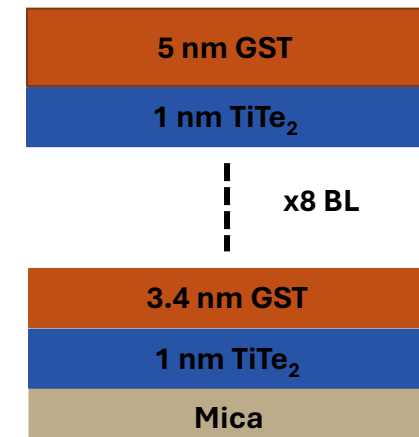
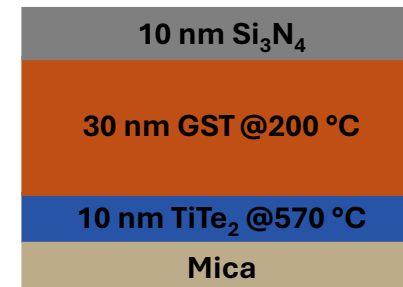
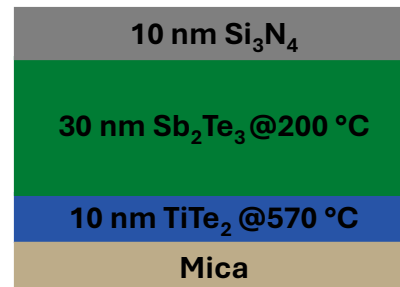
• TiTe_2



Atomic Force Microscopy (**AFM**) images

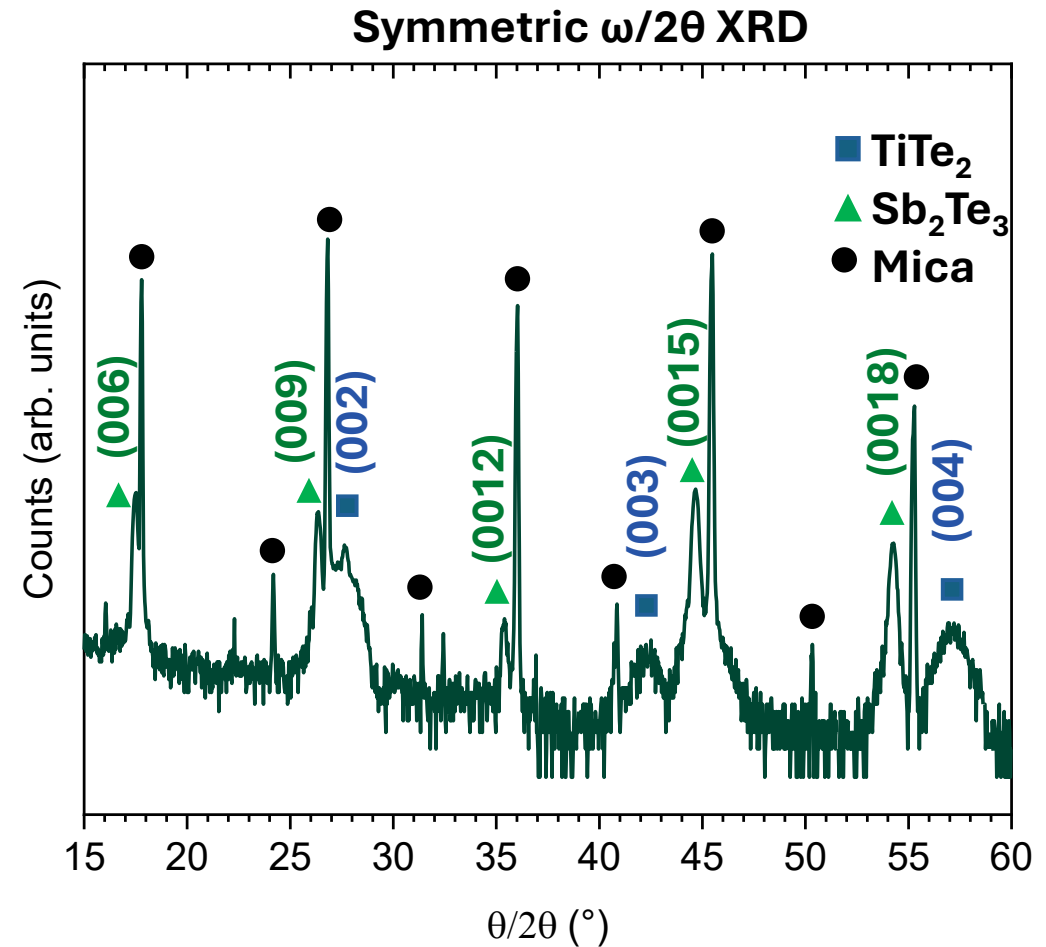
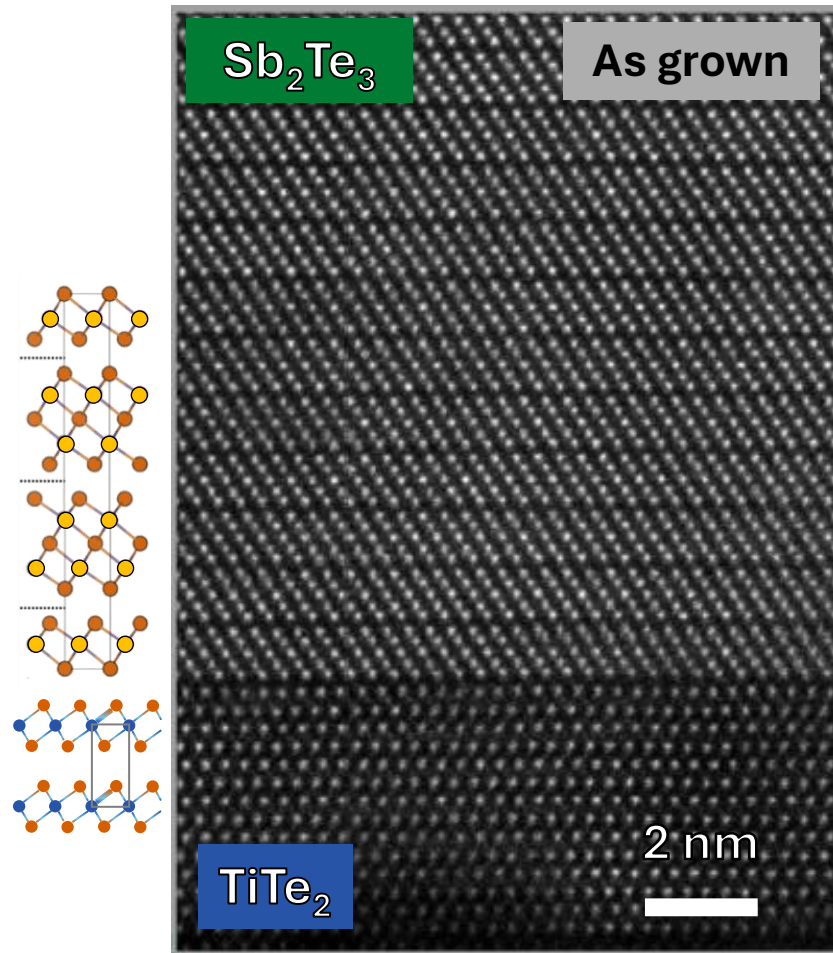


! Different growth windows



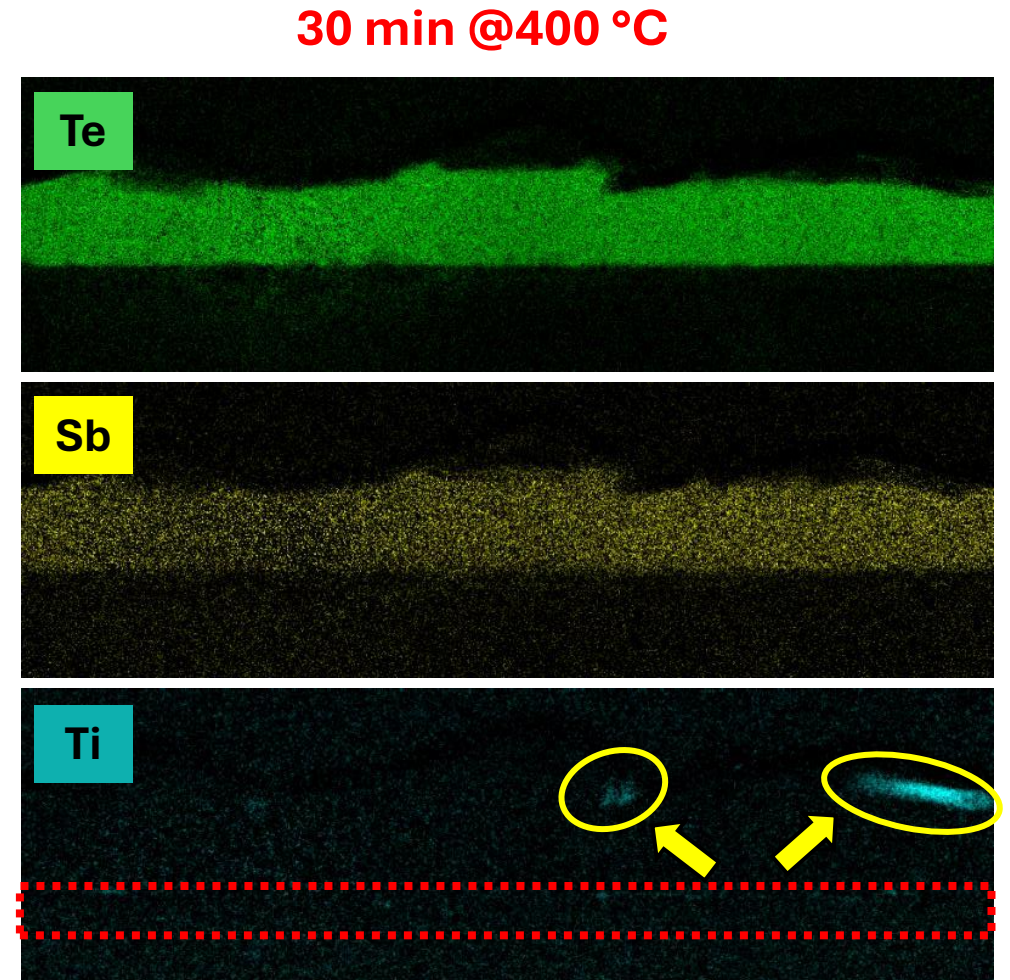
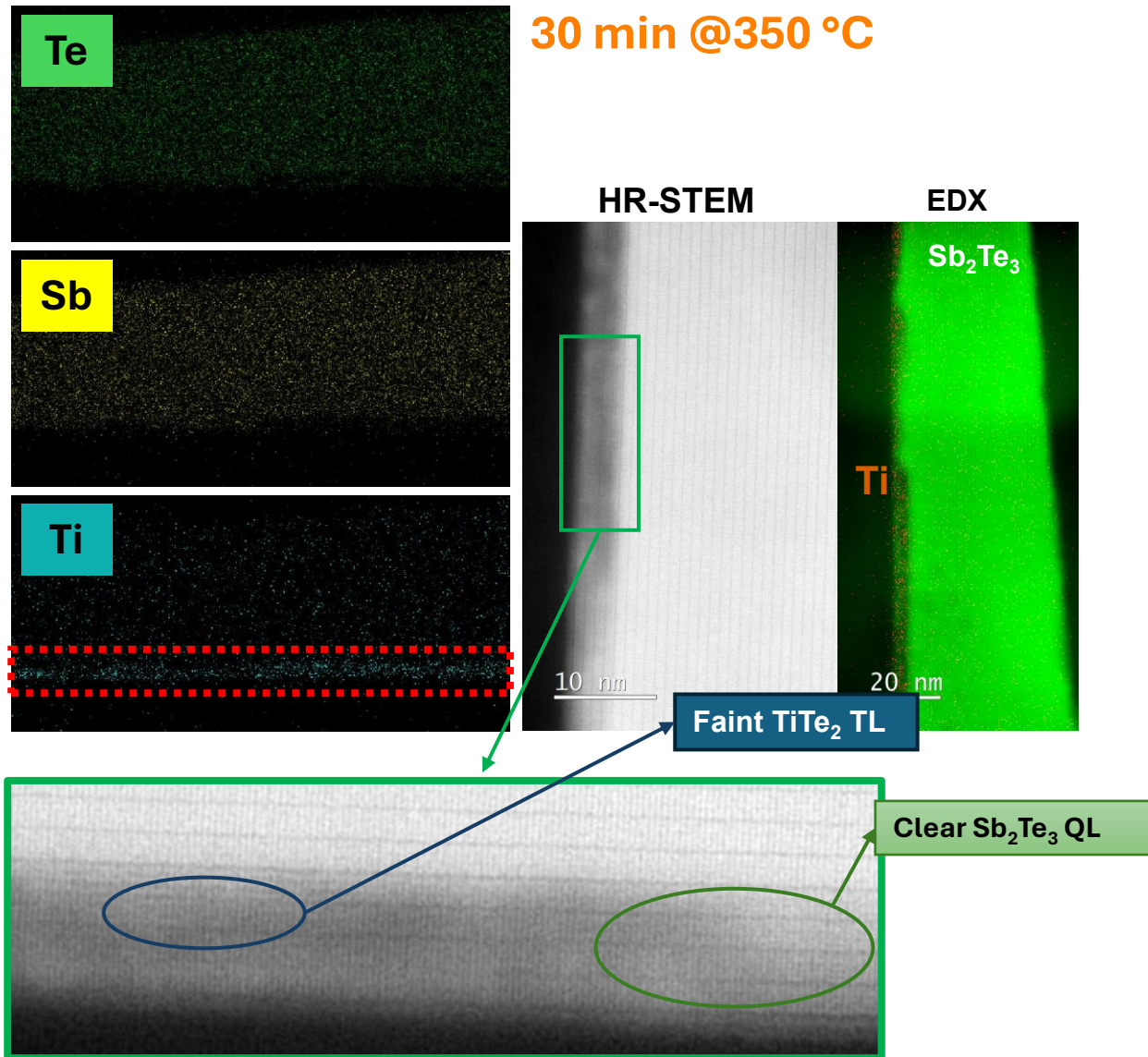
Bilayers growth

High Resolution-Transmission Electron Microscopy (HR-TEM)

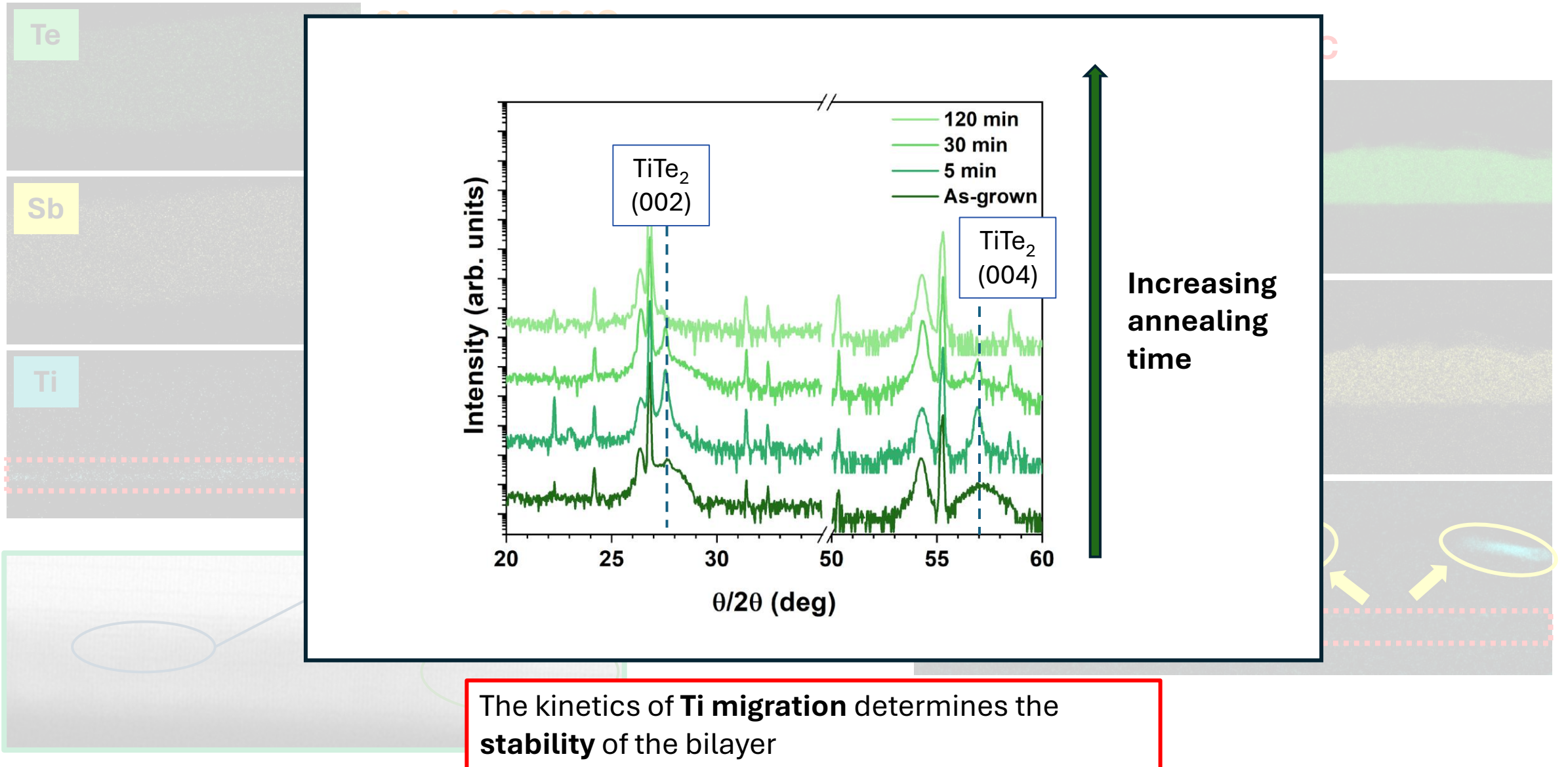


- Highly oriented sample

TiTe₂-Sb₂Te₃ Bilayer

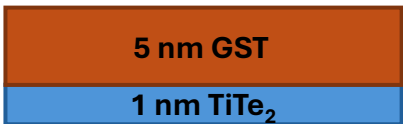
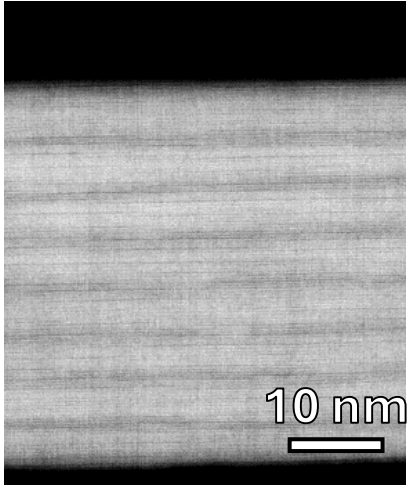


TiTe₂-Sb₂Te₃ Bilayer

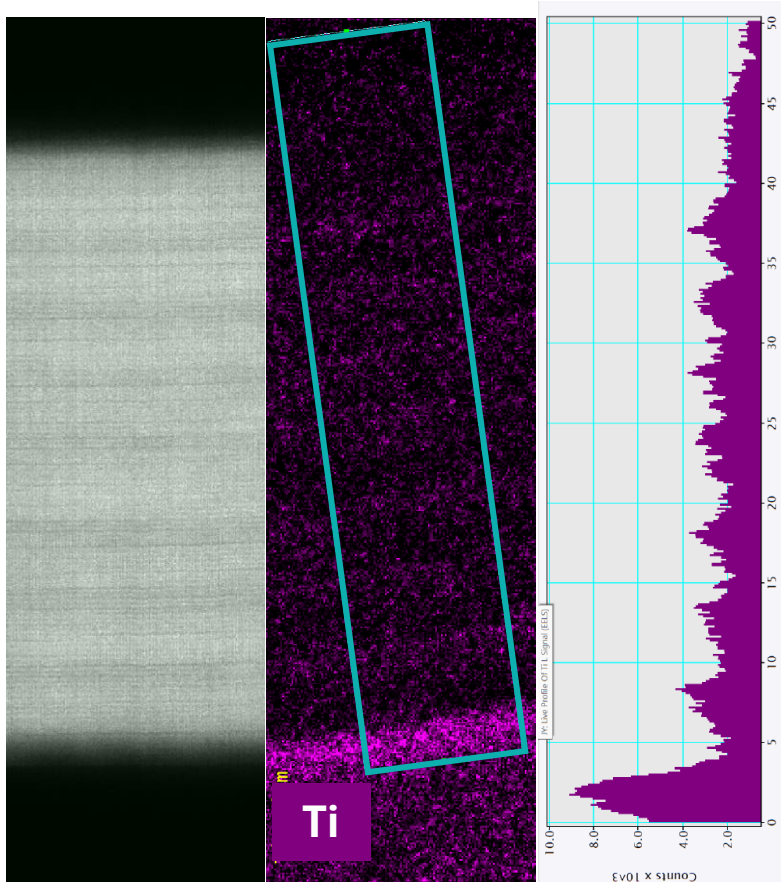
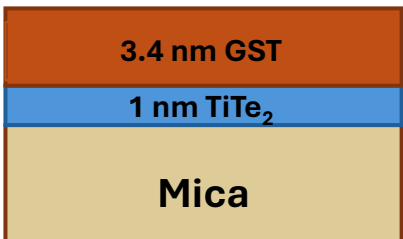


TiTe₂-GST systems

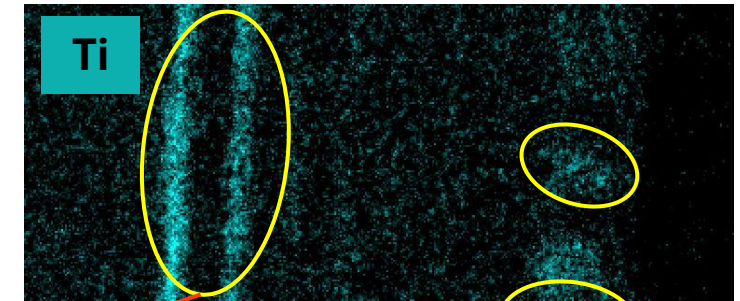
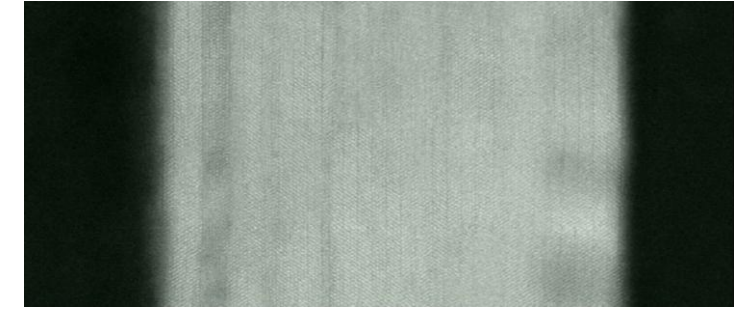
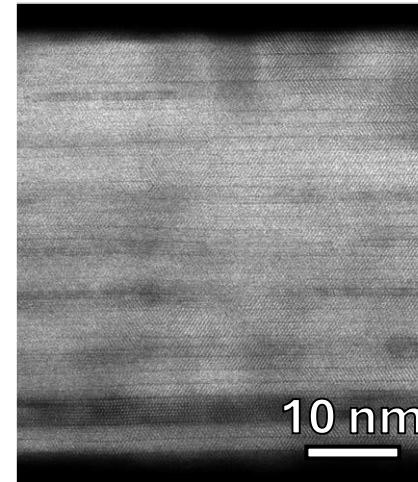
As grown



x8 BL



30 min @350 °C

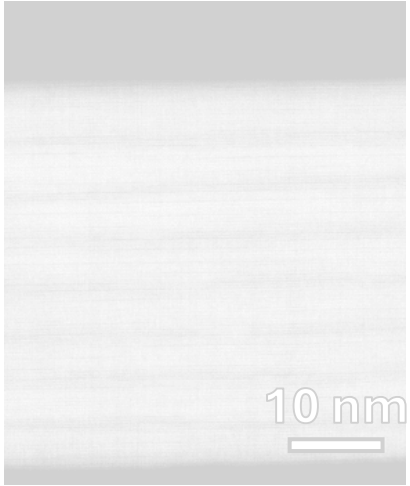


Ti migration towards first TiTe₂ layer increasing Ti signal

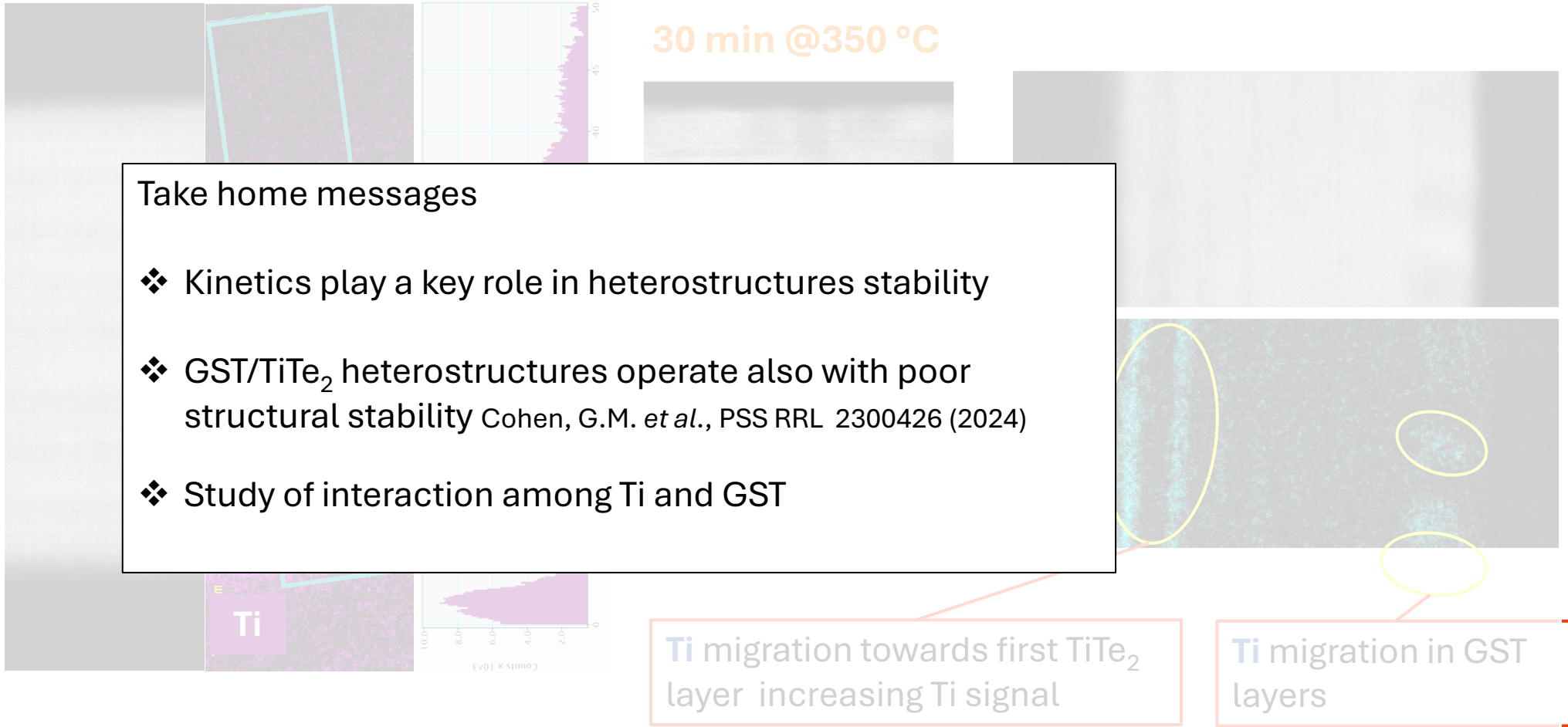
Ti migration in GST layers

TiTe₂-GST systems

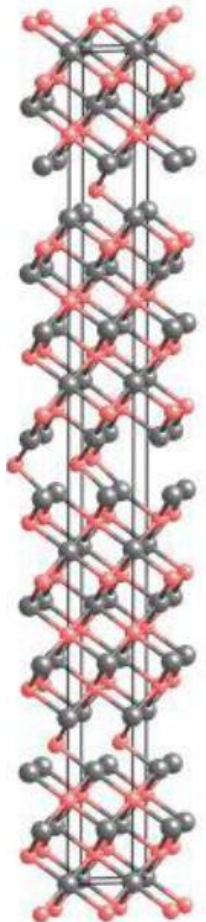
As grown



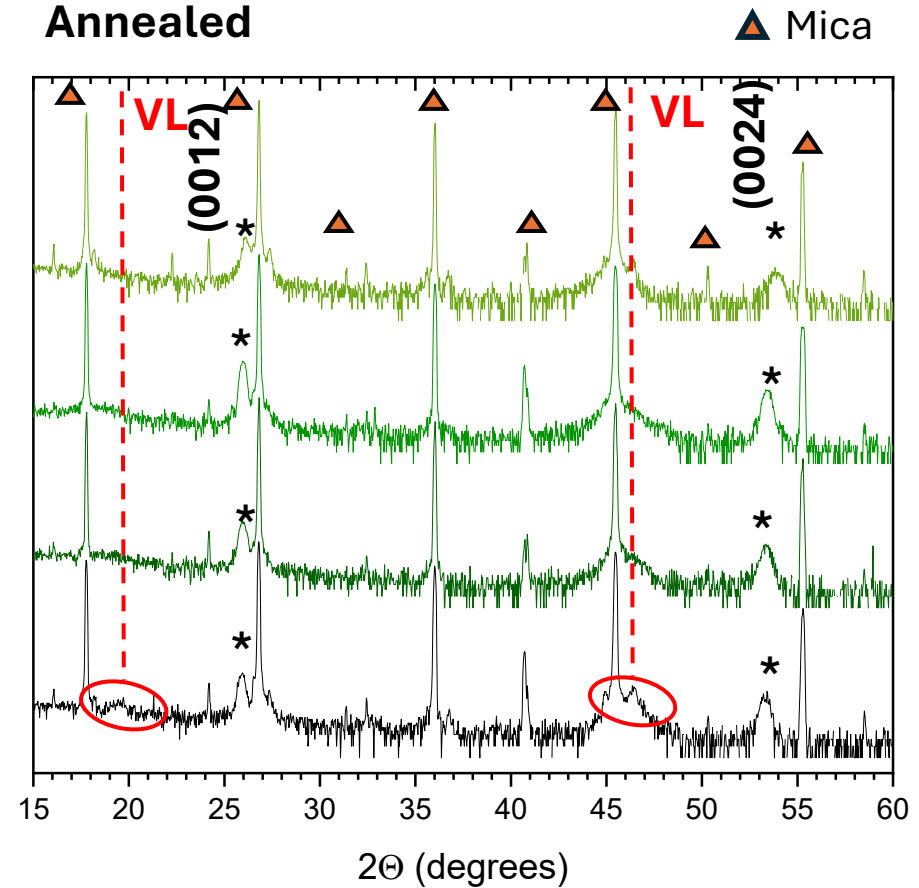
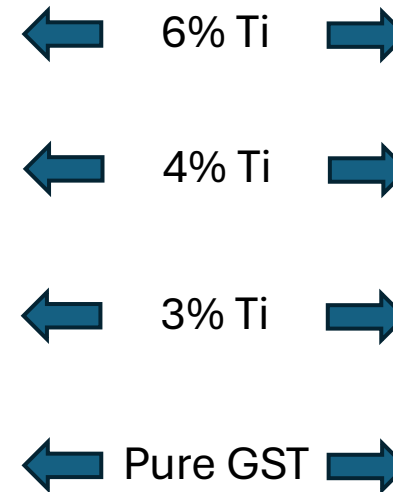
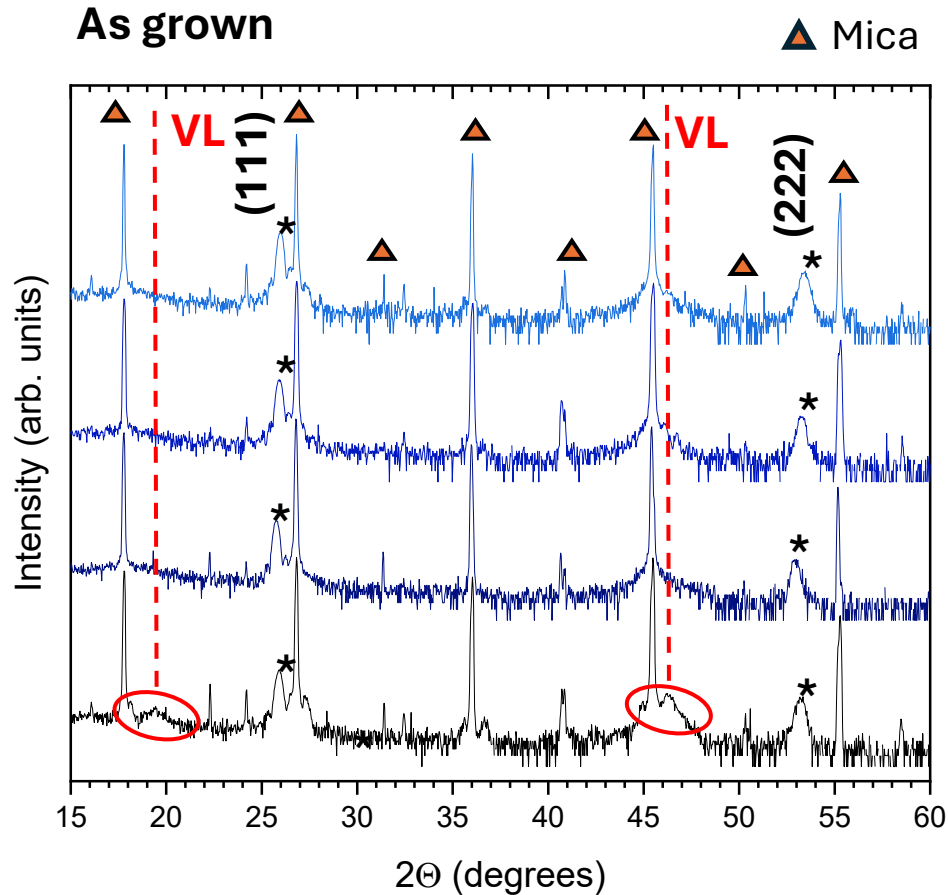
x8 BL



Ti-doped GST



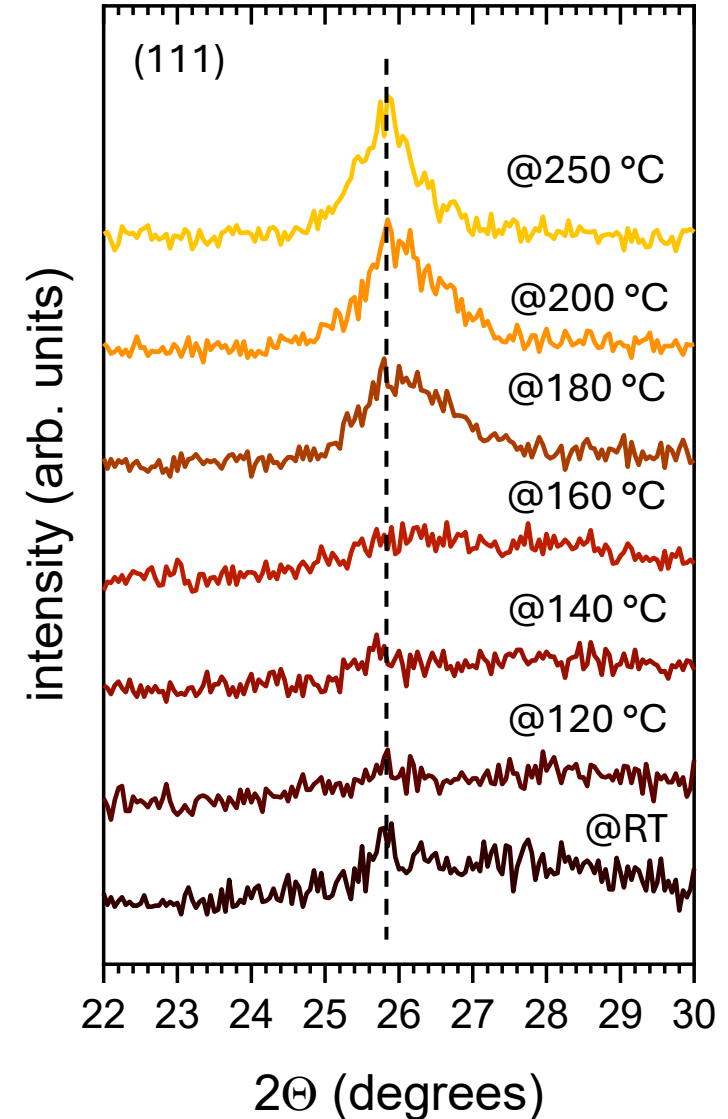
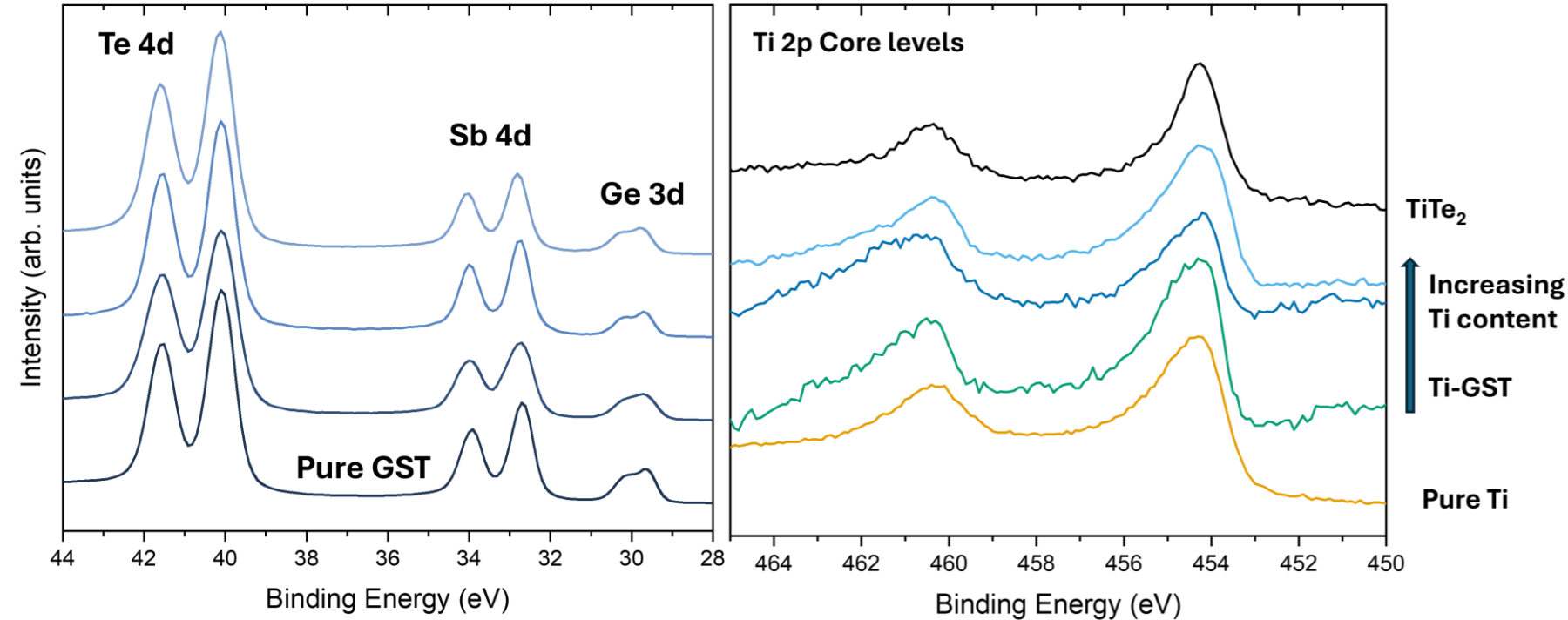
Cubic-GST



- **No evidences of Vacancy Layers** features (red dashed lines) in Ti-GST samples
- **No evidences of secondary compounds** (e.g. TiTe_2) in the samples

Ti-doped GST

X-Ray photoemission Spectroscopy (XPS)

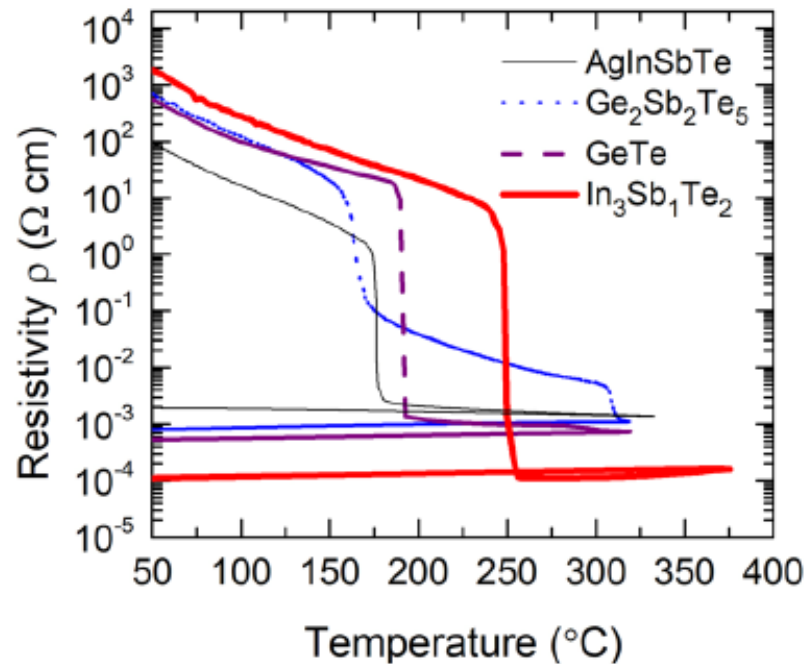


- Evolution of intensity of **111 peak** upon annealing suggest a crystallization temperature between **160 °C** and **180 °C** (Ref. GST: 100-160 °C)

Outlook

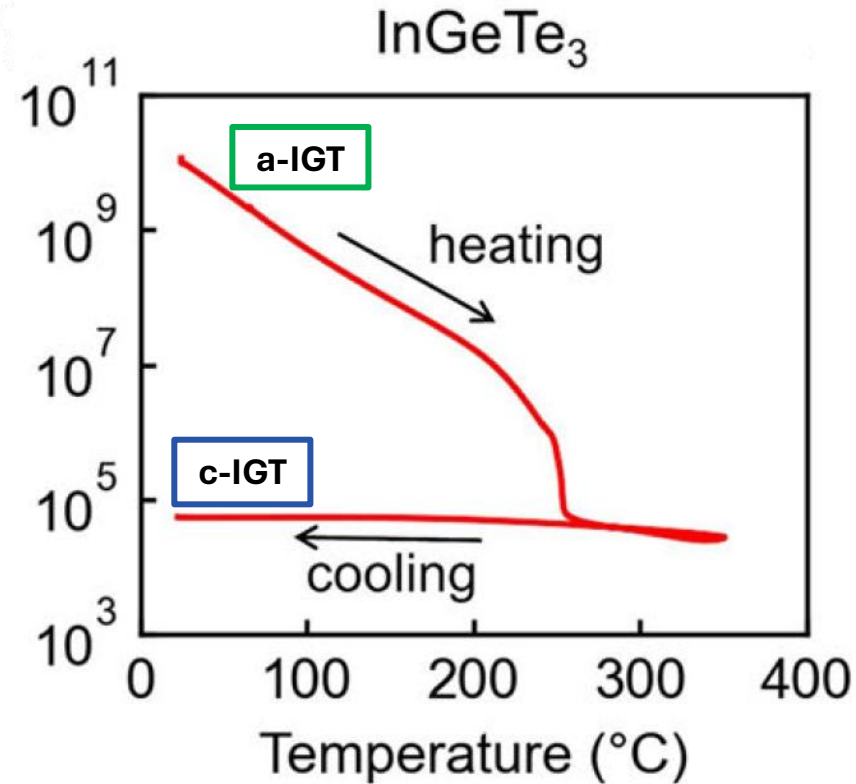
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In-based PCMs

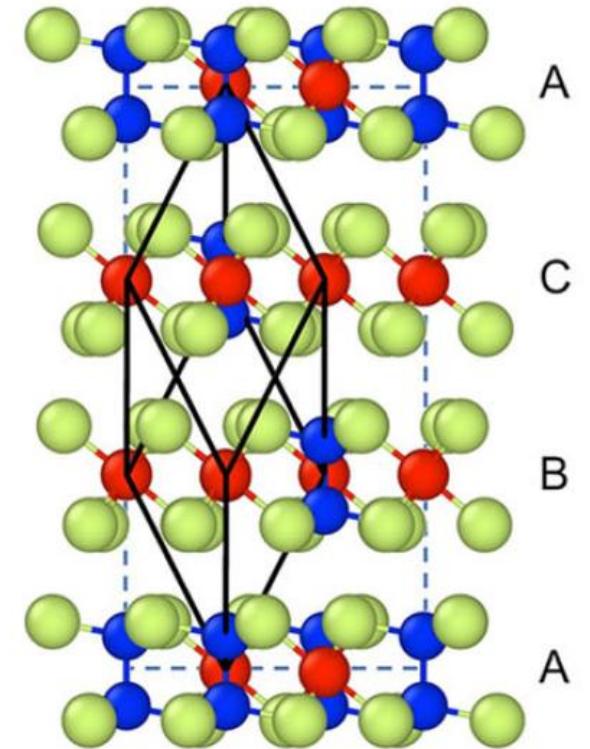


- Higher crystallization temperature, **up to 250 $^{\circ}\text{C}$** for $\text{In}_3\text{Sb}_1\text{Te}_2$

Saxena, Nishant, *et al Scientific reports* 9.1 (2019): 19251.

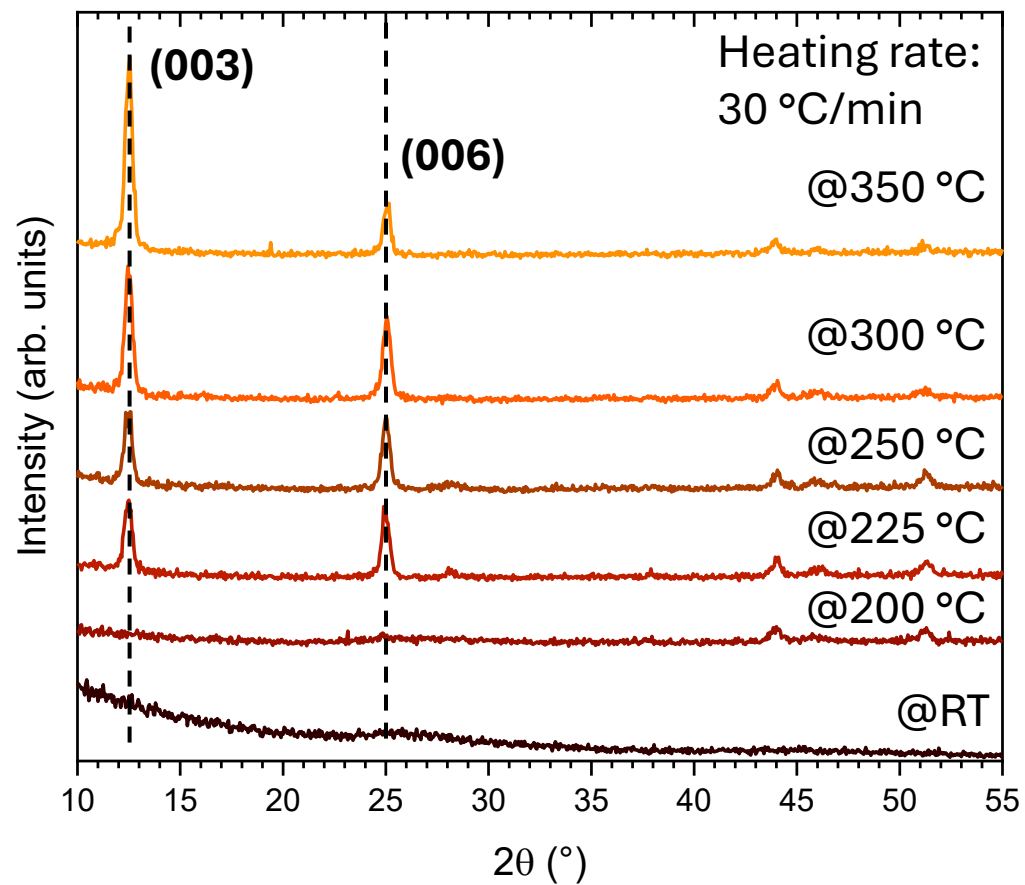


- Huge contrast in resistivity** values among amorphous and crustalline phases (10^{10} vs 10^5)
- Layered structure for InGeTe_3 (IGT-113)

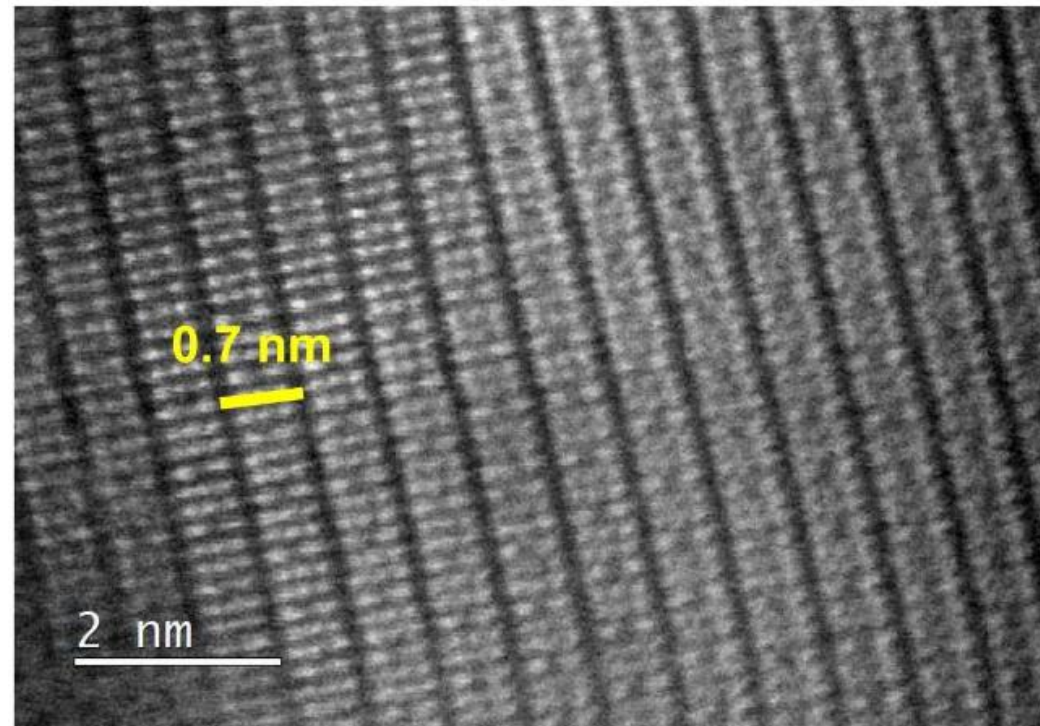


Sun, Suyang, *et al. npj Computational Materials* 10.1 (2024): 189.

InGeTe₃

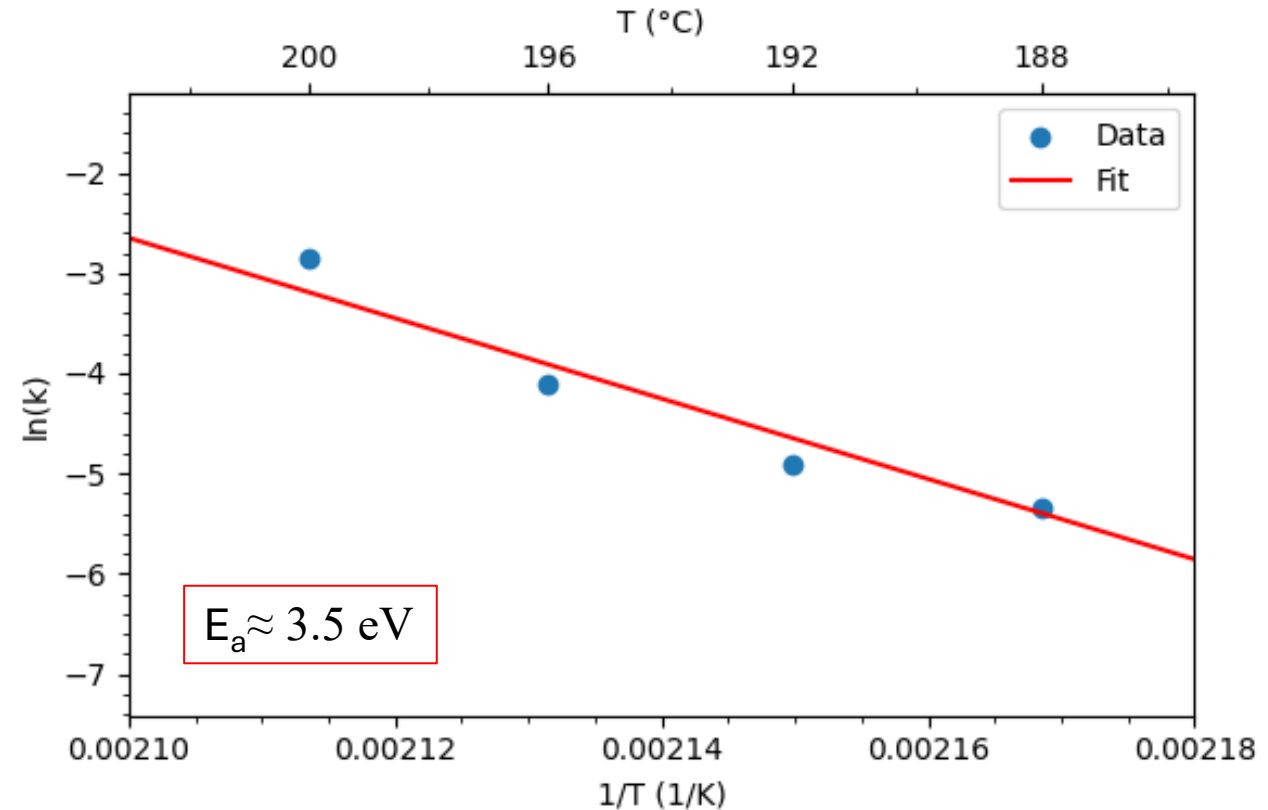
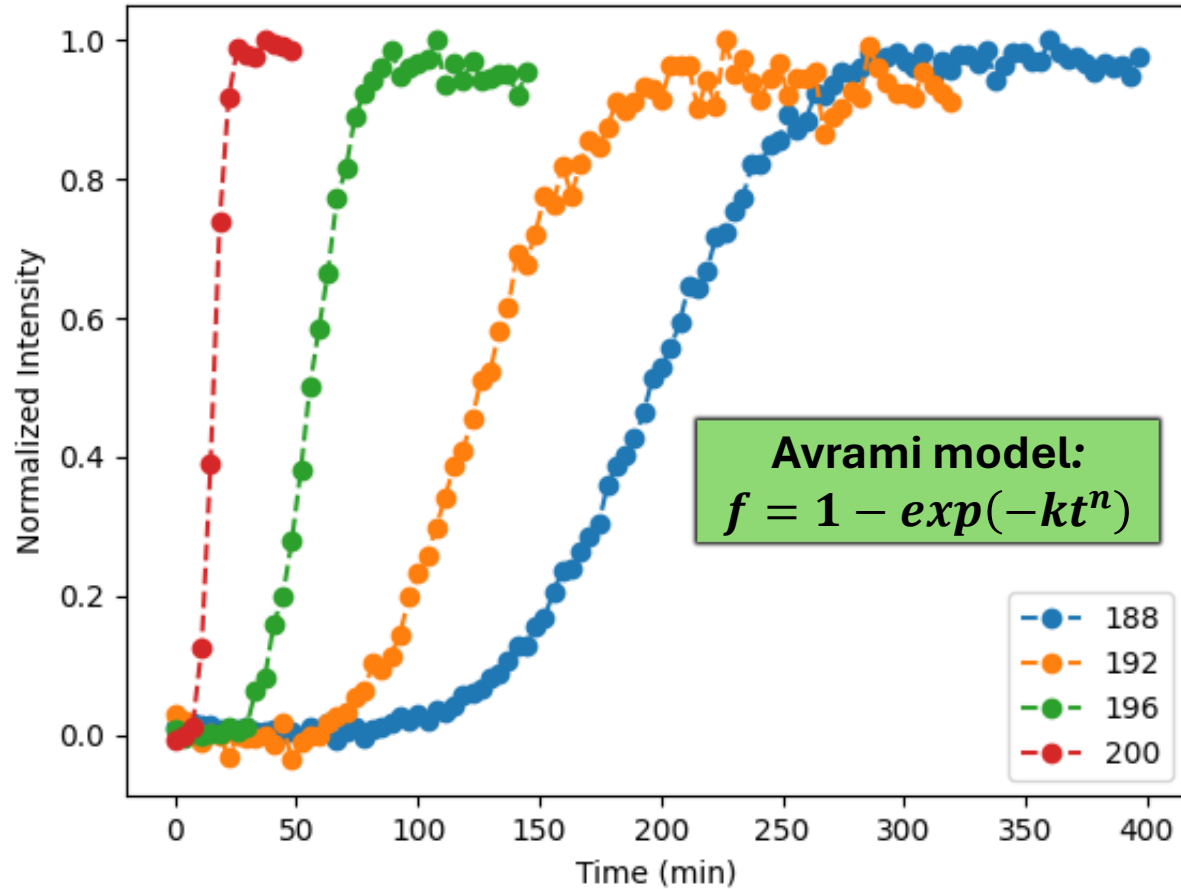


TEM image



- Evidences of **layered structure** in IGT-113
- Presence of (00l) peaks as most intense peaks confirm high orientation of the samples
- Crystallization temperature between 200 °C and 225 °C

Crystallization of InGeTe_3



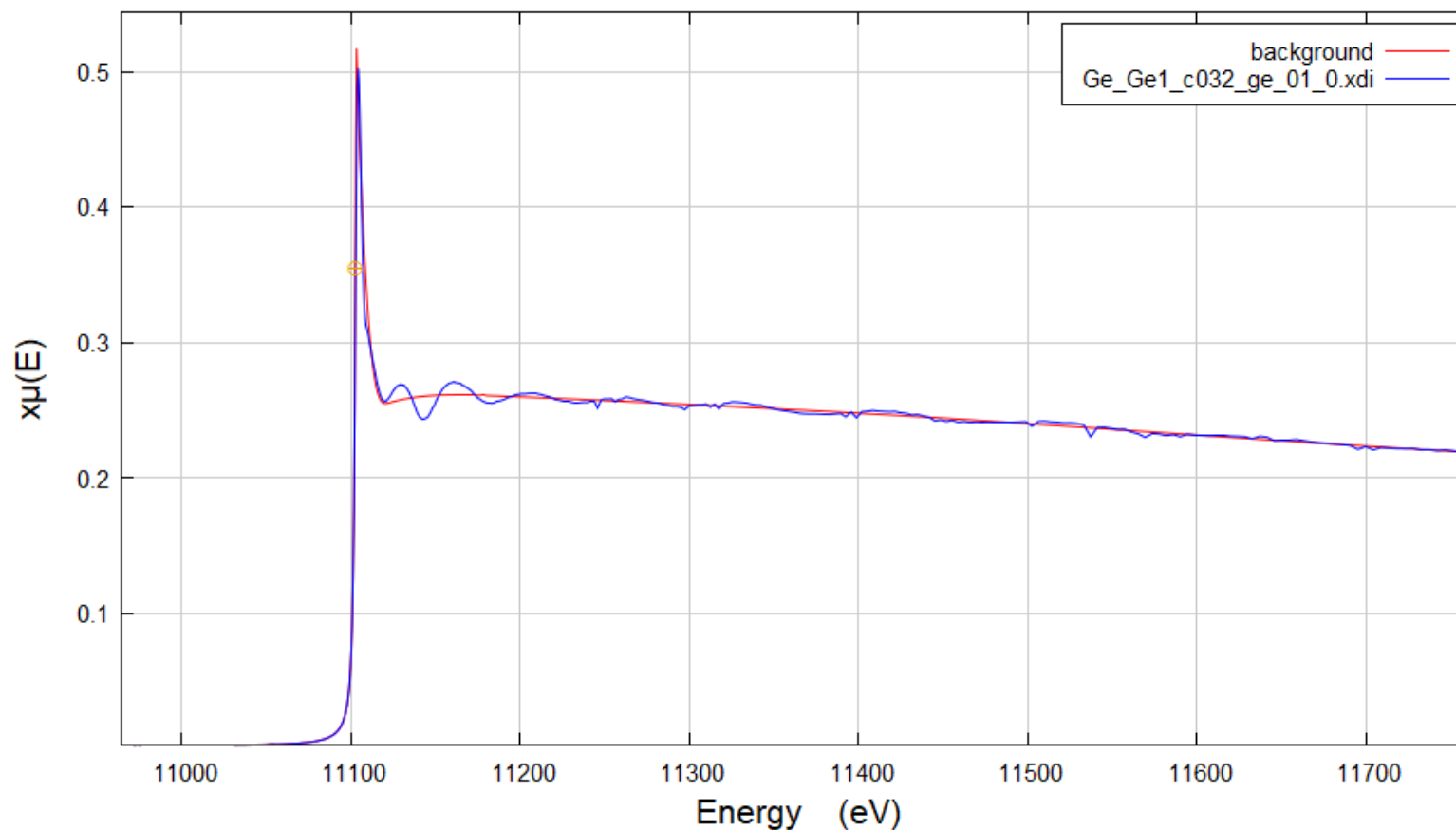
- Avrami model allows an interpretation of the crystallization process
- K follows an Arrhenius-Like law
- Parameter: intensity of **main crystalline peak** during isothermal process

What's next?



Ge absorption edge– IGT @195 °C

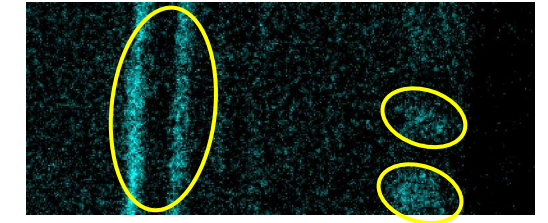
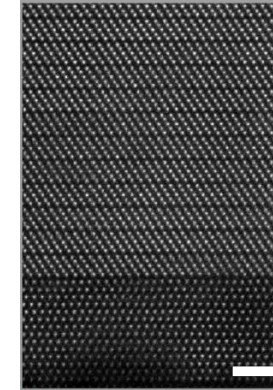
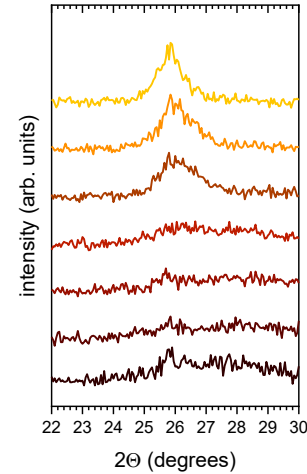
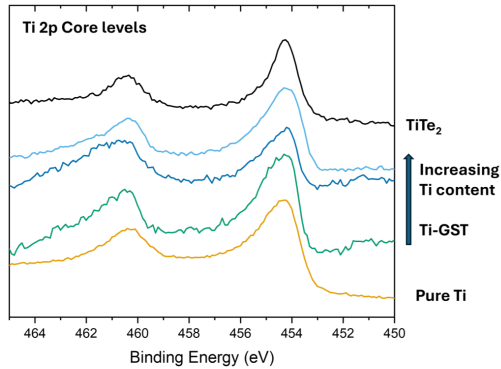
Experiment MA6822



- X-ray absorption (**EXAFS**) measurements to investigate the coordination of atoms during phase transition (amorphous to crystalline)
- **Ongoing** data analysis

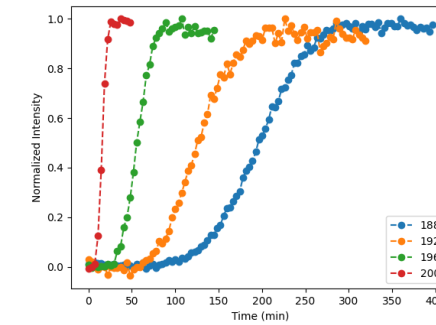
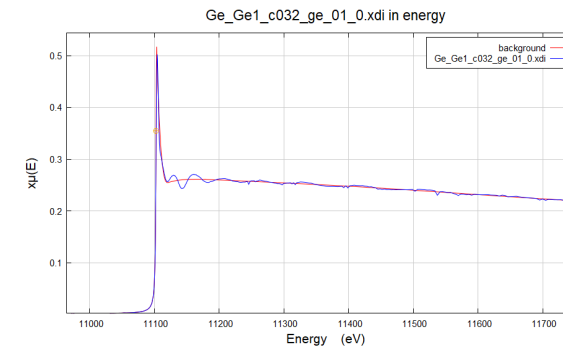
Conclusion

- Growth of high quality and oriented epitaxial TiTe_2 , Sb_2Te_3 and GST single layers and heterostructure: thermal stability has been tested



- The effect of Ti incorporation in GST matrix has been investigated

- Highly oriented layered IGT has been grown, and the study of crystallization process has started and is ongoing



Aknowledgements



Dept. of Physics

- ❖ Prof. Fabrizio Arciprete
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- ❖ M. Sc. Adriano Diaz Fattorini
- ❖ Dr. Flavia Righi Riva

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- ❖ Dr. Valentina Mussi

Catania

- ❖ Dr. Antonio Massimiliano Mio



Dept. of Physics

- ❖ Prof. Ernesto Placidi



LISA beamline

- ❖ Dr. Francesco D'Acapito



- ❖ Dr. Stefano Colonna

PRIN2020 – EMPHASIS - *NEuroMorPHic devices bASed on chalcogenIde heteroStructures*

Project funded by the Italian Ministry of University and Research

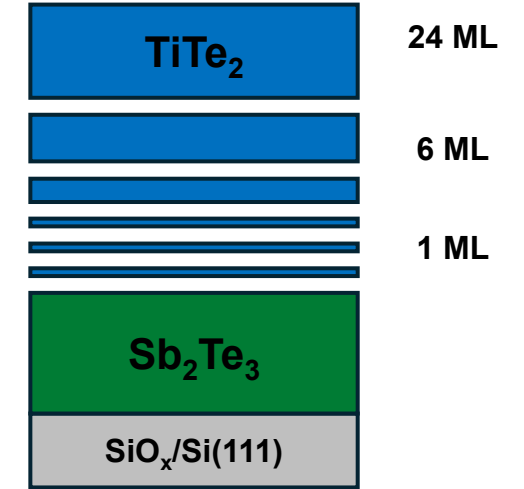
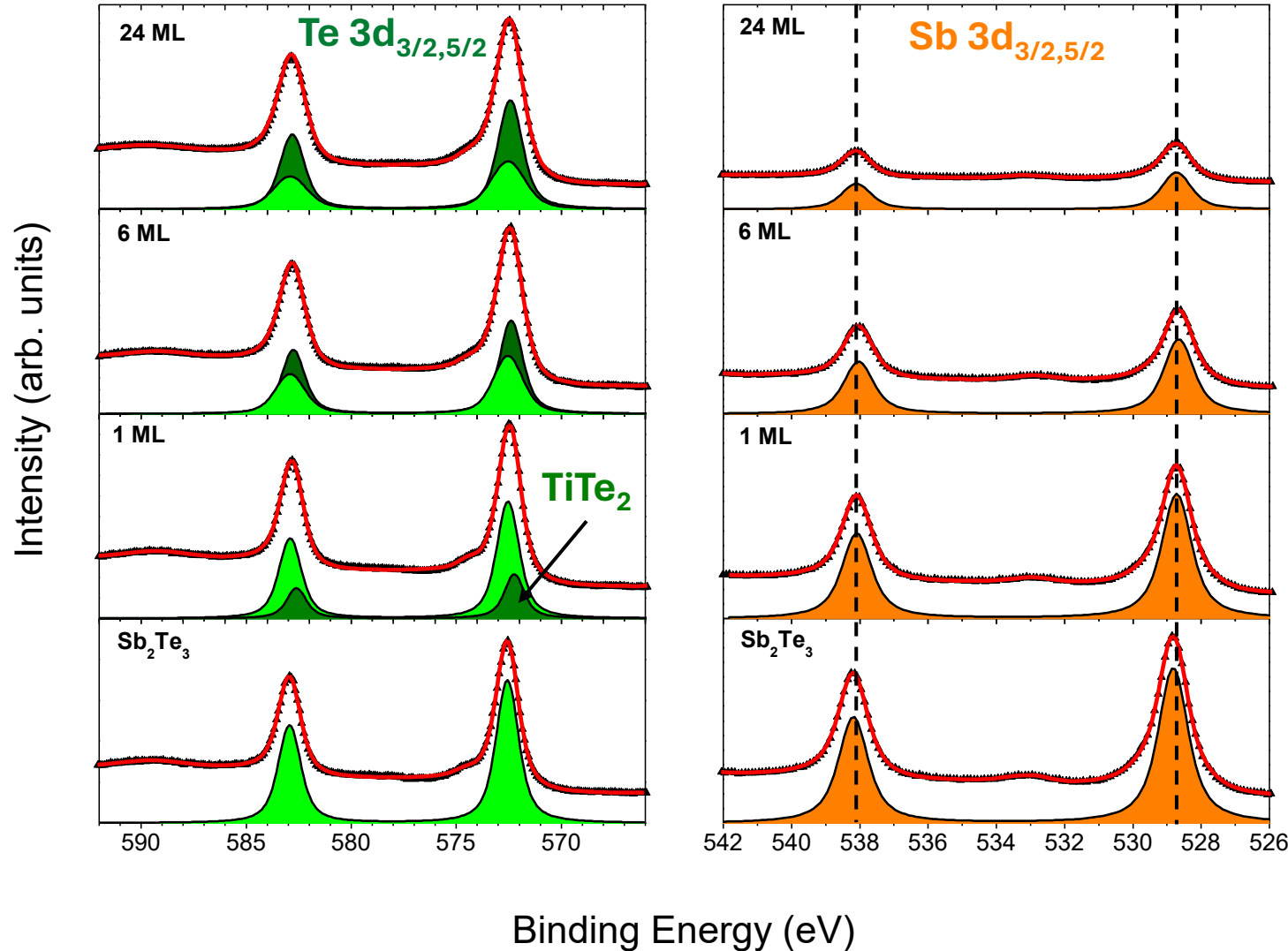
**Thank you for your
kind attention**

Backup Slide

TiTe₂-Sb₂Te₃ Bilayer

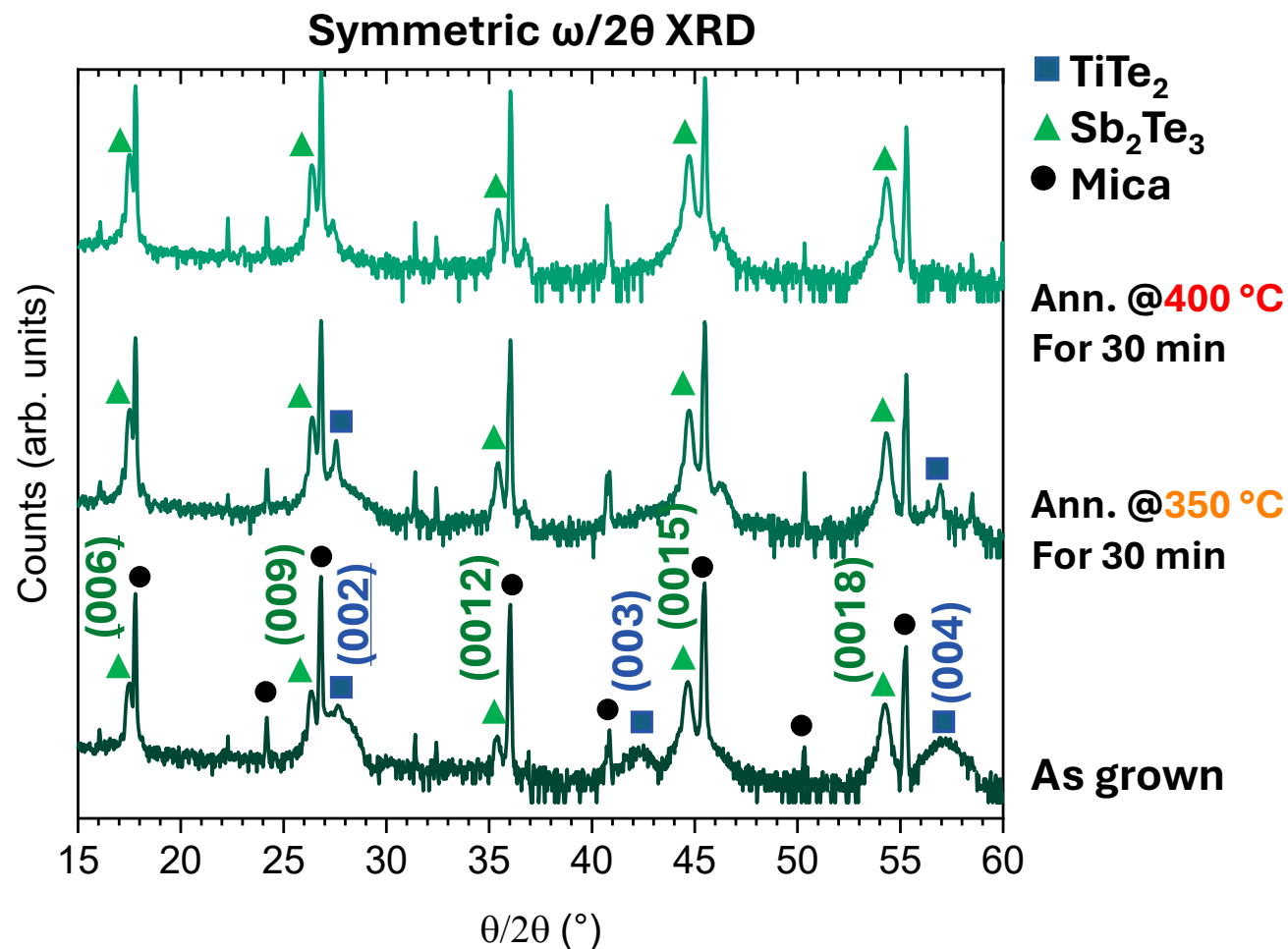
In situ X-Ray
Photoemission Spectroscopy

Mg K α = 1253.6 eV



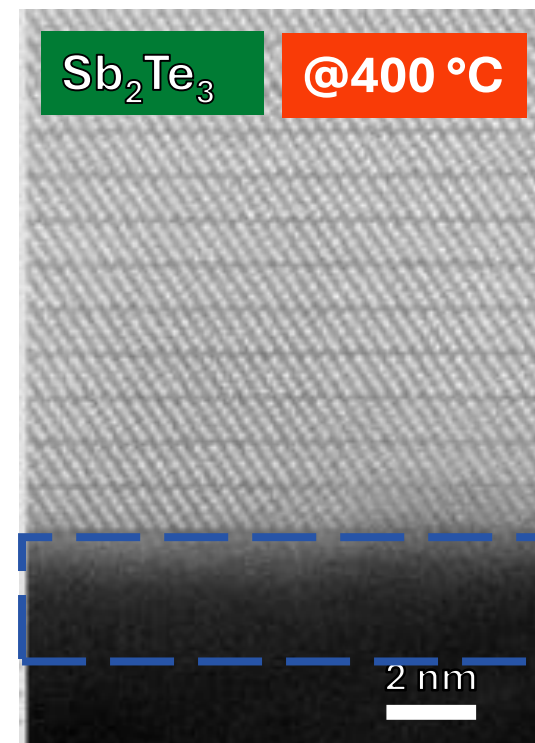
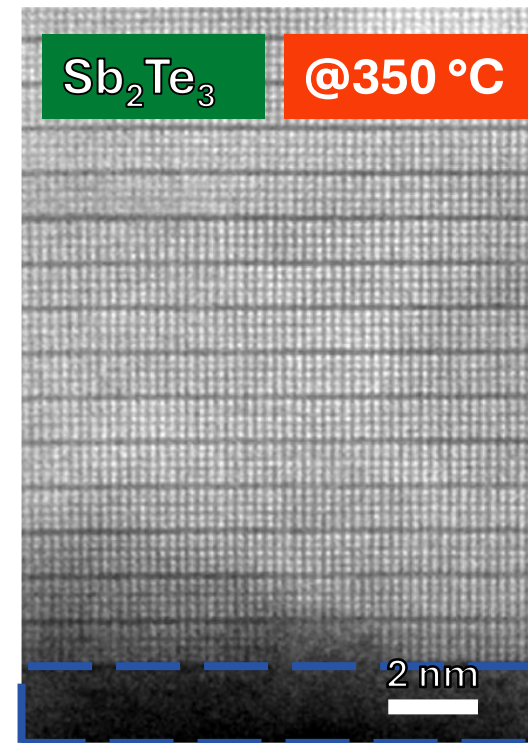
- **Step-by-step** growth and characterization on **Si** substrate
- Fitting deconvolution of the contributions of the two layers
- **No Intermixing** phenomena and Sb migration detected at the interface

TiTe₂ – Sb₂Te₃ annealing



✓ Sb₂Te₃ displays out-of-plane orientation

✗ TiTe₂ peaks disappear increasing annealing T

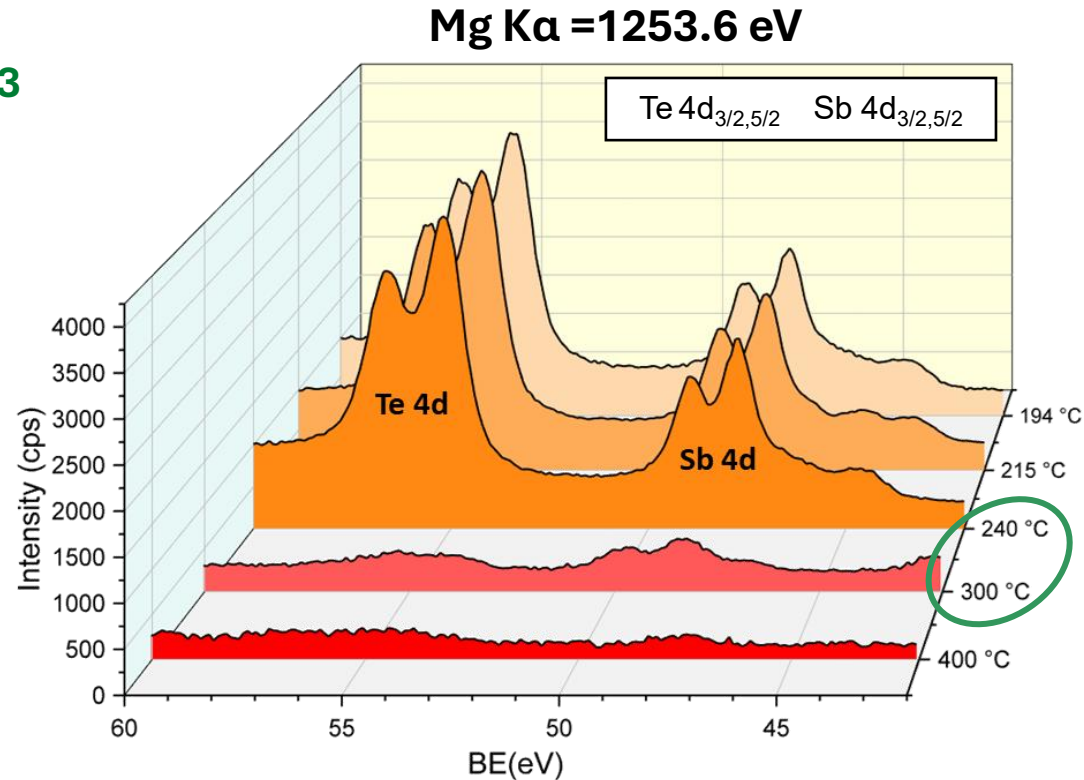


✓ Sb₂Te₃ displays quintuple layers

✗ No TiTe₂ structures

Epitaxial films

- Sb_2Te_3**

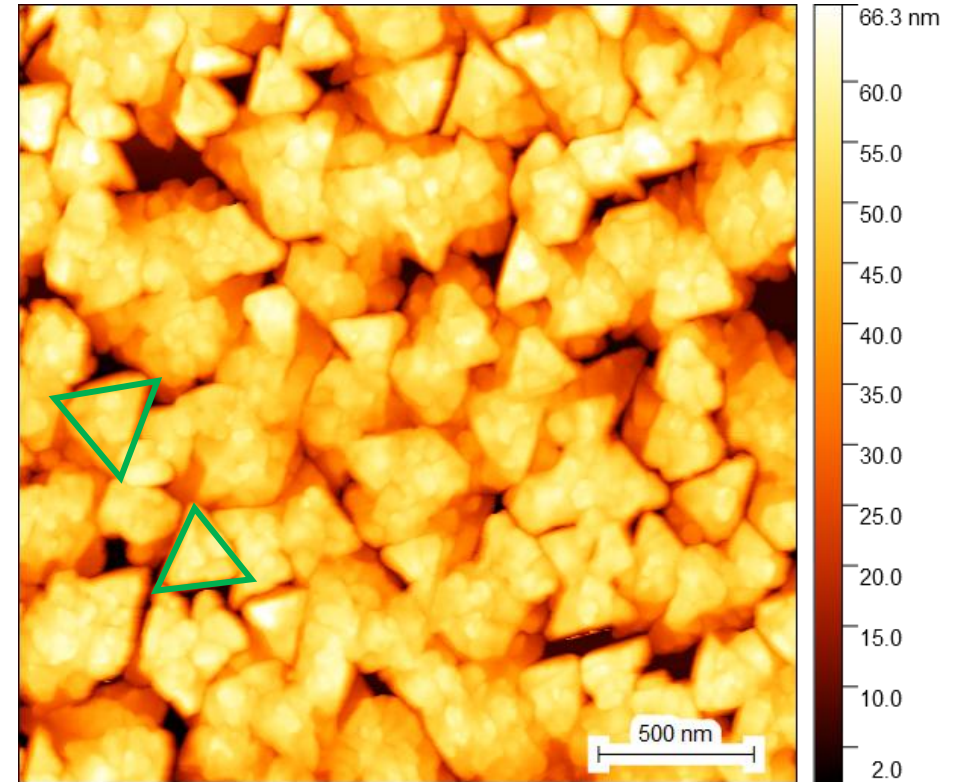


- Epitaxial Sb_2Te_3 can be obtained for $T_{\text{growth}} \leq 250\text{ °C}$
- Composition evaluation from **Te** and **Sb** core levels via XPS:

- Sb:Te=**2.2:3.1**

$$x_i = \frac{I_i/S_i}{\sum_i (I_i/S_i)}$$

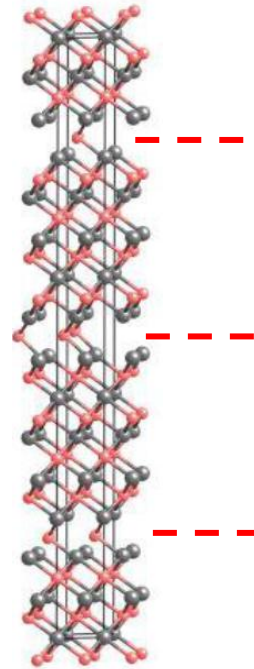
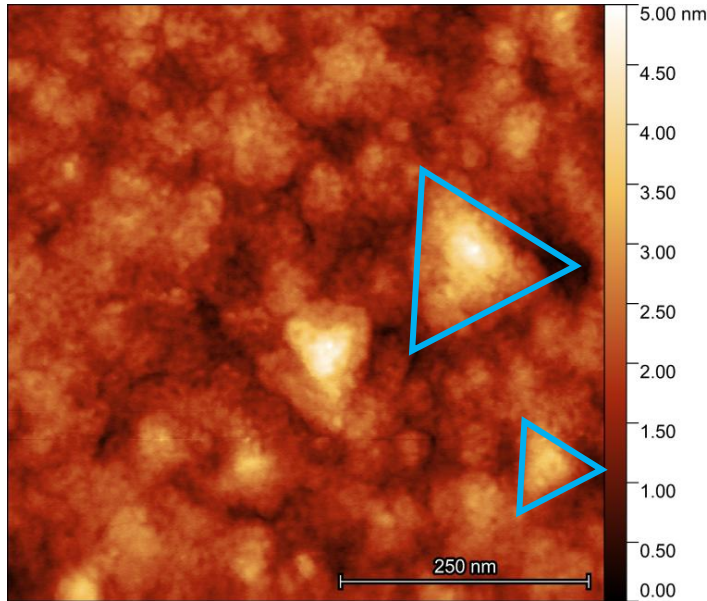
S_i from C.D.Wagner, *et al.*, Surf. Interfaces Anal.(1981)



Epitaxial films

- **GST**

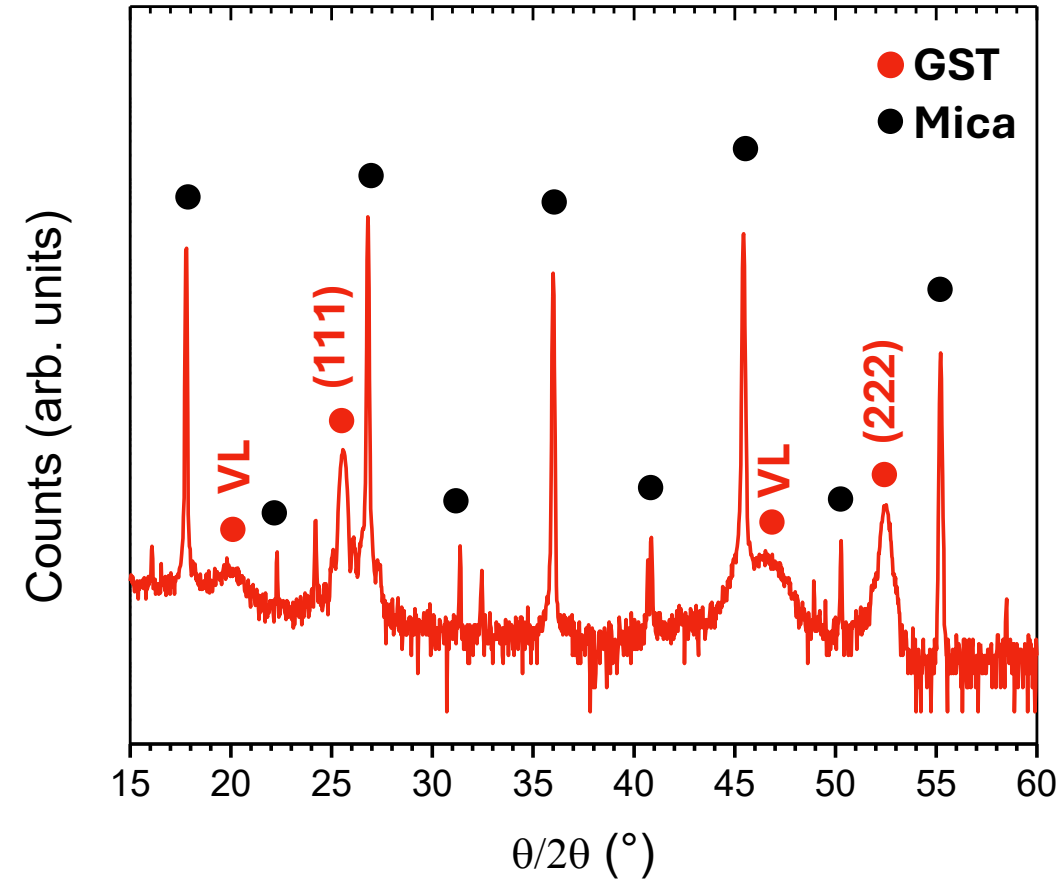
Bragaglia, V. et al. *AIP Advances* 7.8 (2017).



Vacancy
Layers (VL)

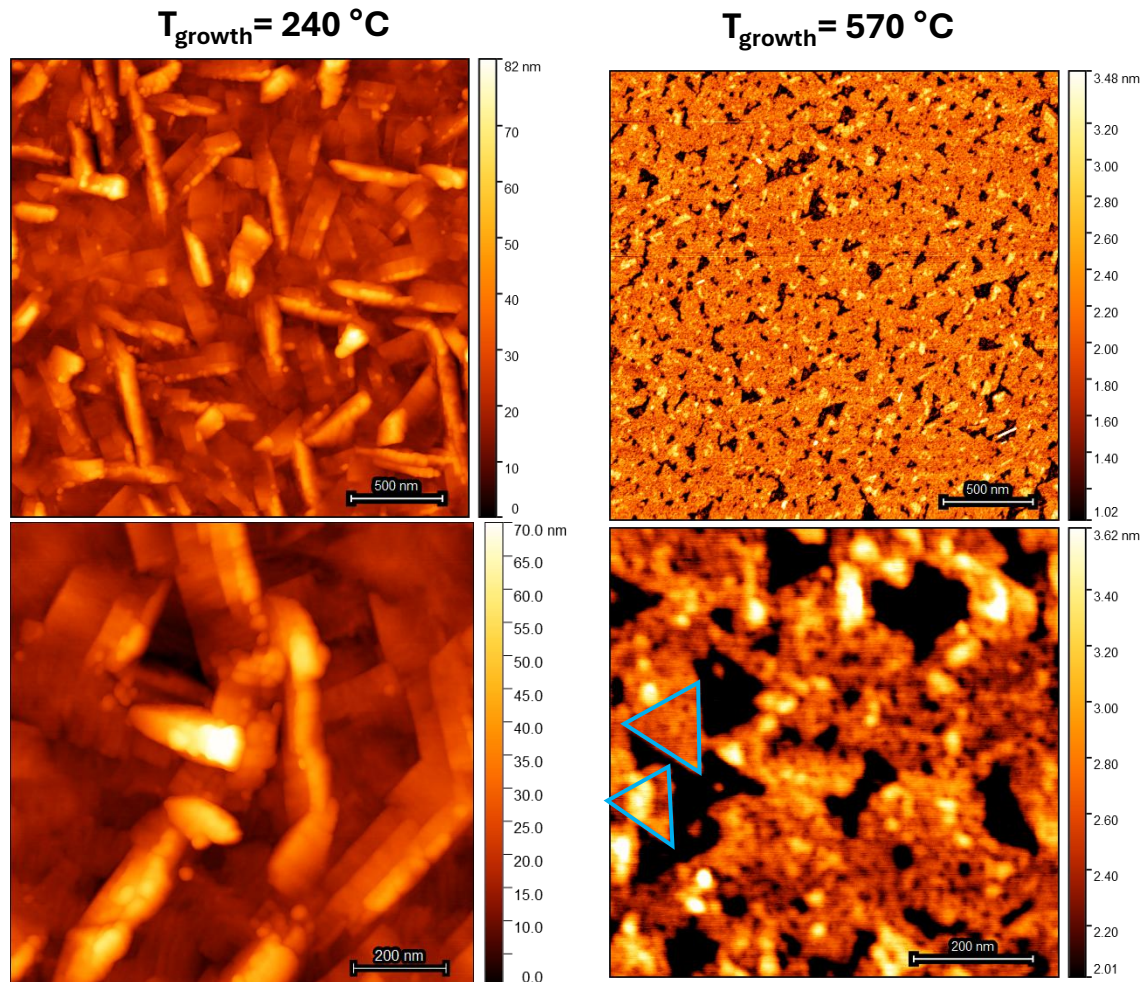
- Epitaxial **GST** can be obtained for same Sb_2Te_3
 - $T_{\text{growth}} (\leq 250^\circ\text{C})$
- Composition evaluation from XPS:
 - Ge:Sb:Te=1:2:4

Symmetric $\omega/2\theta$ XRD

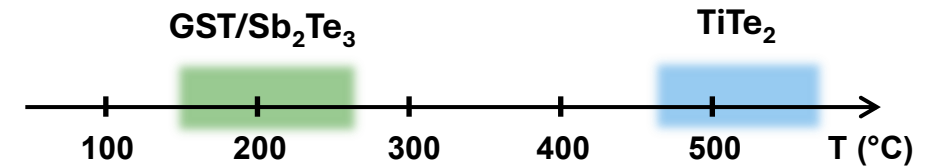


Epitaxial films

- TiTe_2

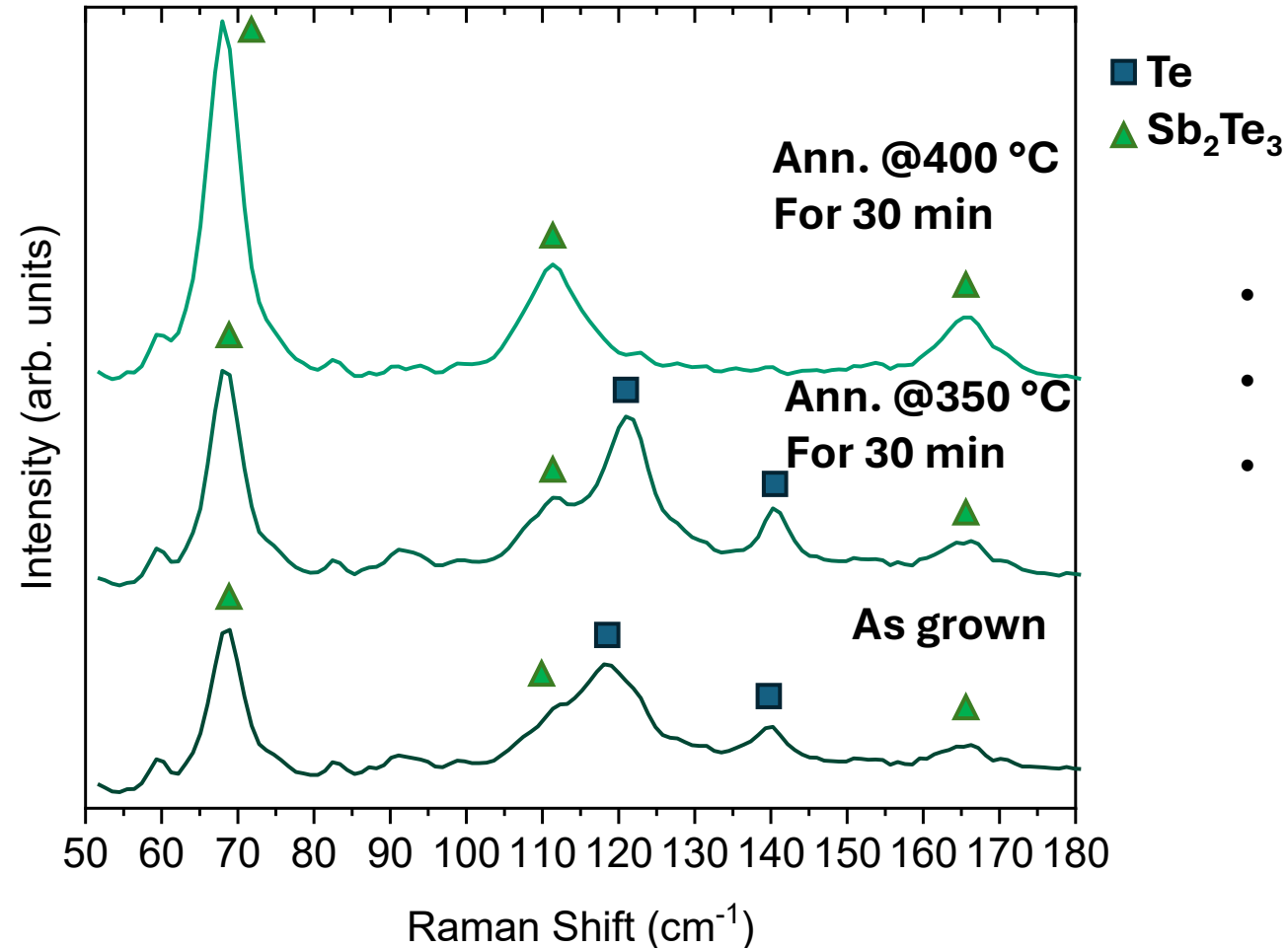


- Epitaxial TiTe_2 can be obtained for $T_{\text{growth}} > 450\text{ }^\circ\text{C}$



! **Different** growth windows

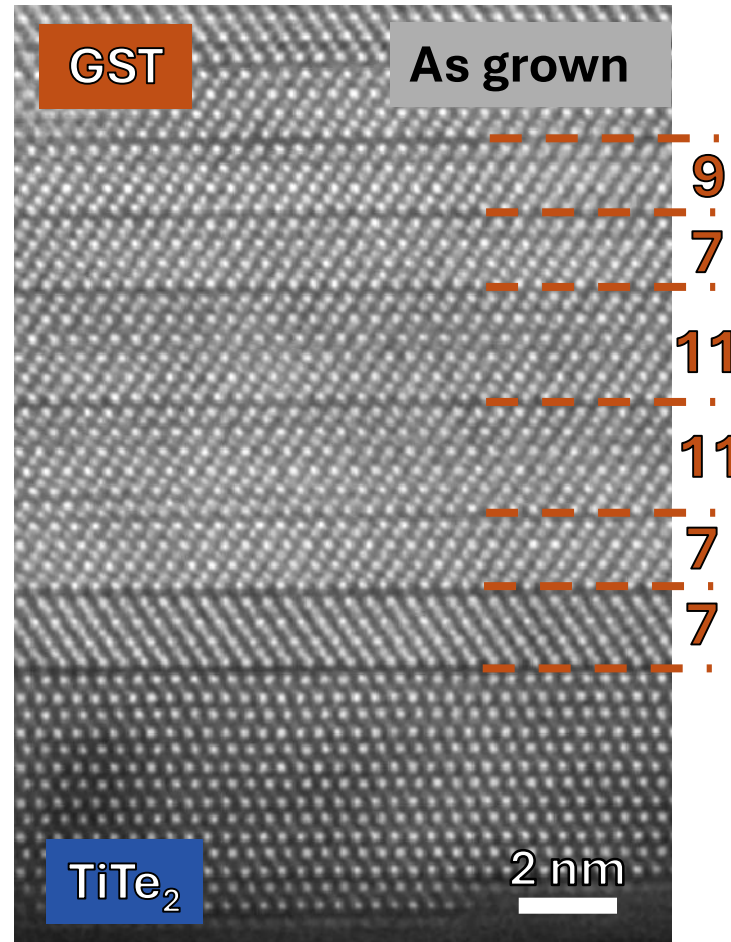
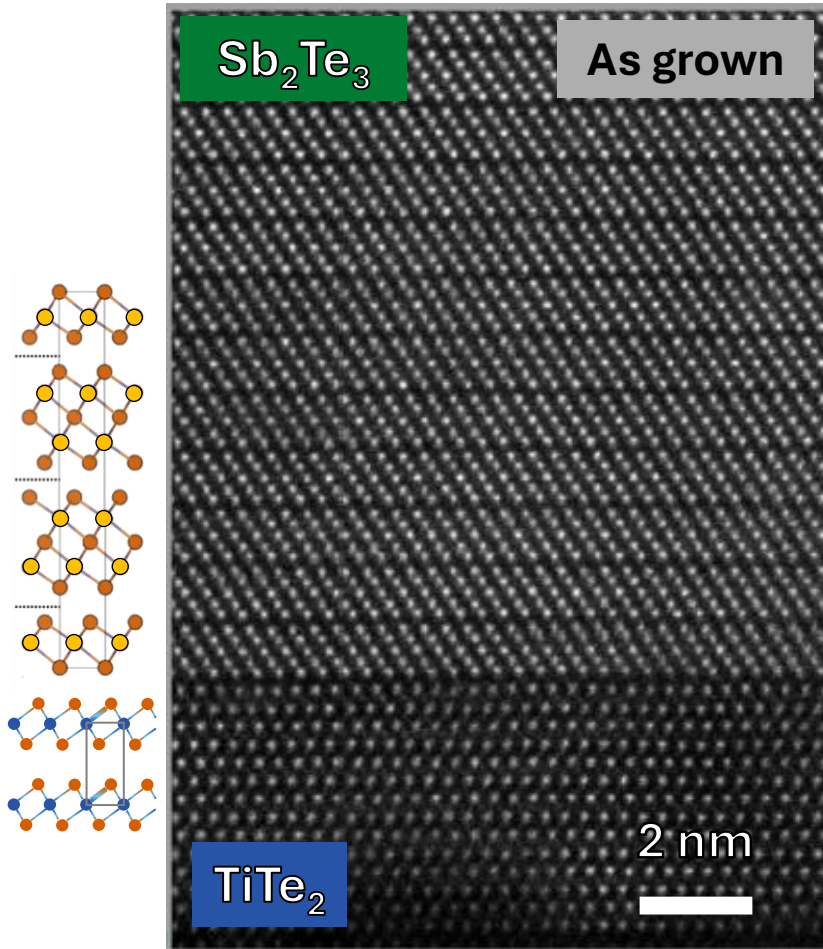
Epitaxial bilayers



- Typical Sb₂Te₃ Raman modes
- Te instead TiTe₂ features
- Extinction of Te modes after 400 °C annealing

Bilayers growth

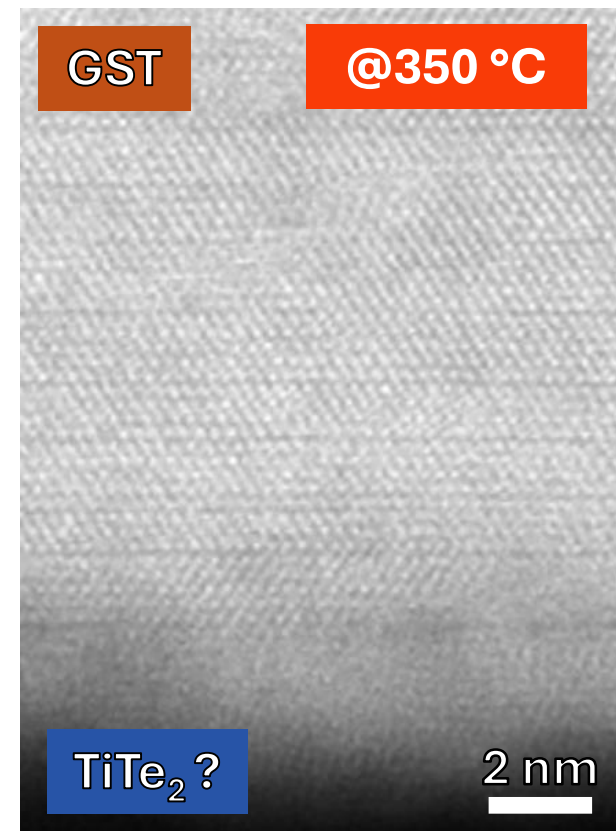
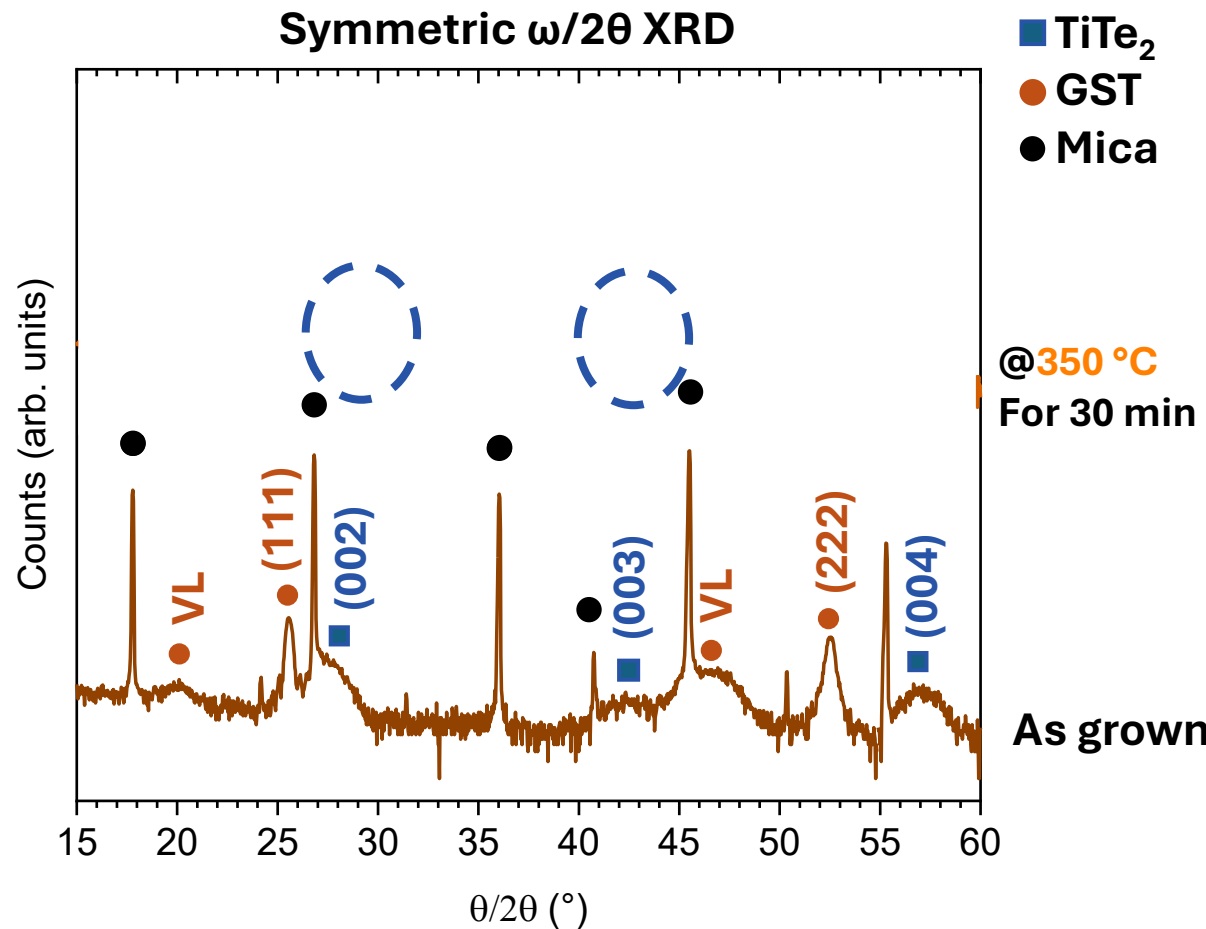
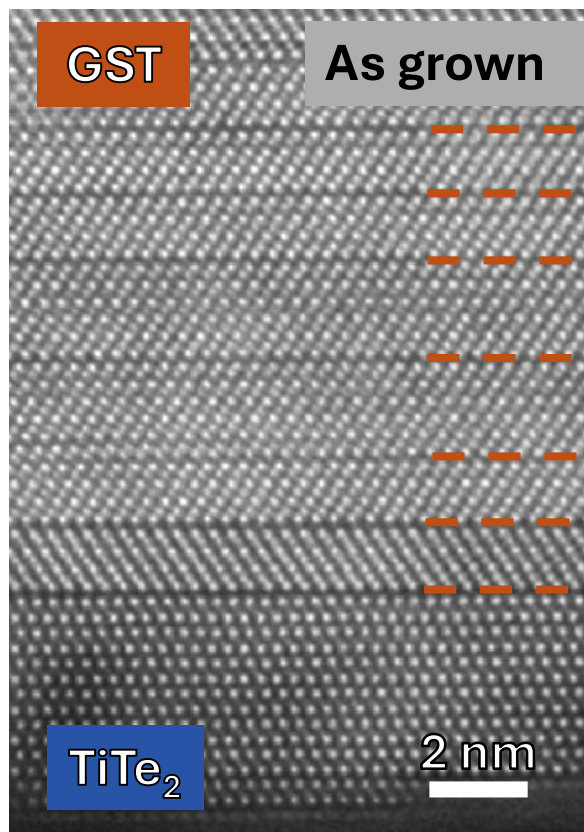
High Resolution-Transmission Electron Microscopy (HR-TEM)



- ✓ **Sharp interface** between TiTe_2 and PCMs
- Evidence of **trilayers** and **quintuple layers**
- ✓ **No intermixing or segregation**

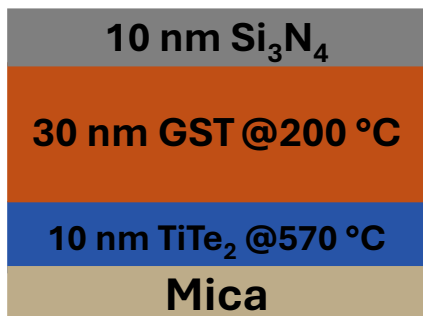
TiTe₂-GST systems

- Epitaxial growth of Sb₂Te₃/TiTe₂ and GST/TiTe₂ systems

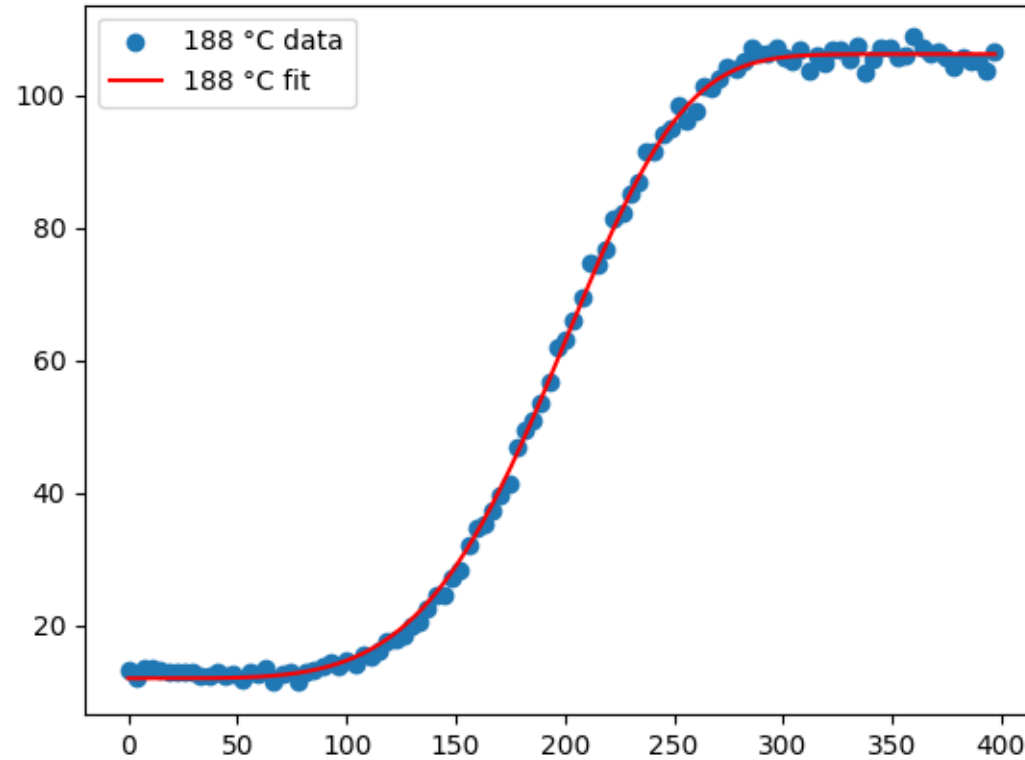


- TEM images

- ✓ GST and TiTe₂ displays out-of-plane orientation with clear evidence of MLs @RT
- ✗ No evidence of TiTe₂ and TLs upon annealing !!!



InGeTe₃



↑
Increasing Ti
content
Ti-GST